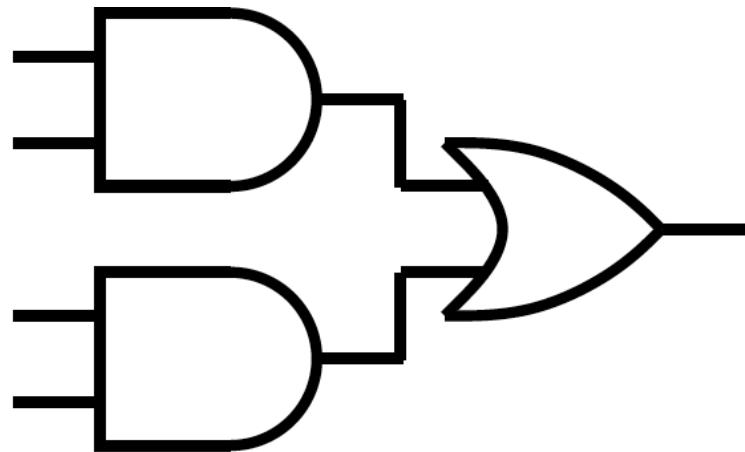


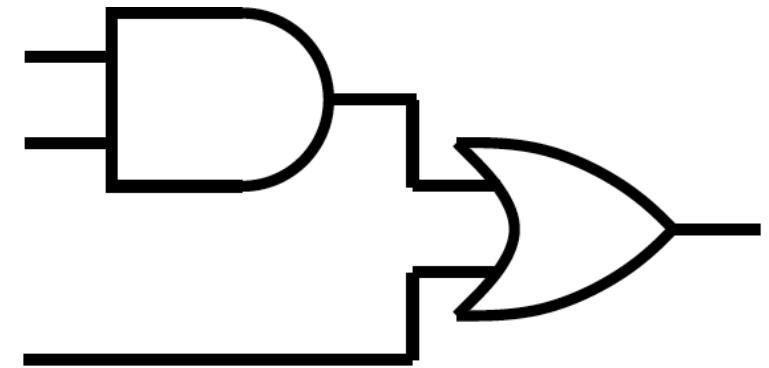
# ESE535: Electronic Design Automation

Day 24: April 22, 2015  
Statistical Static Timing Analysis

# Delay PDFs? (2a)



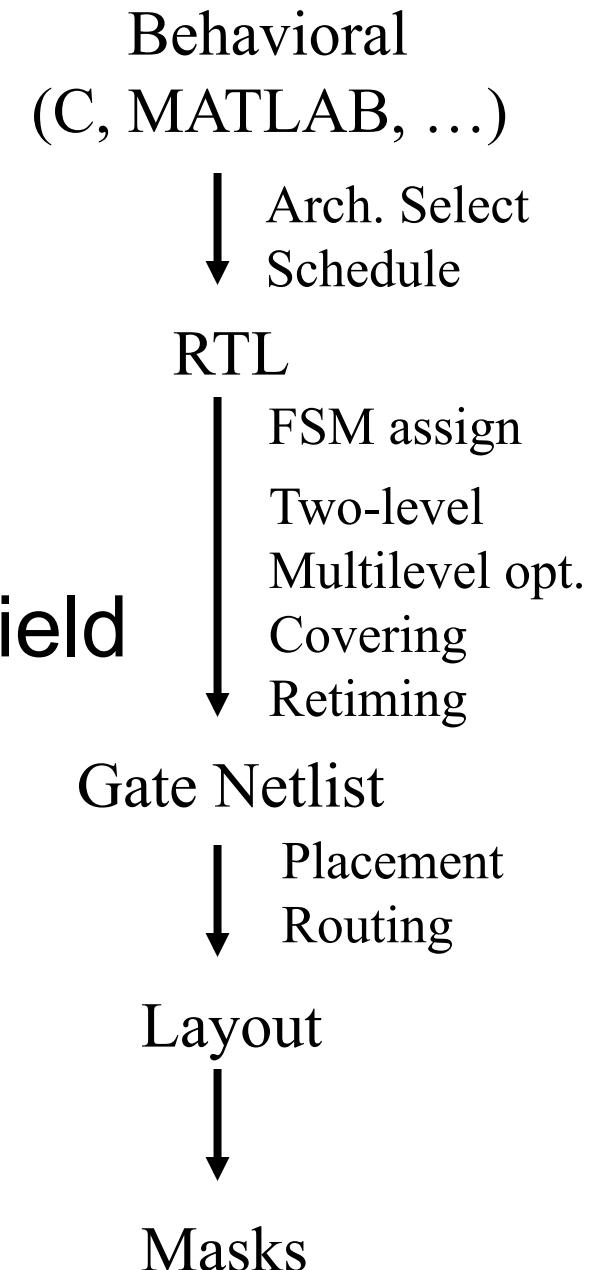
A



B

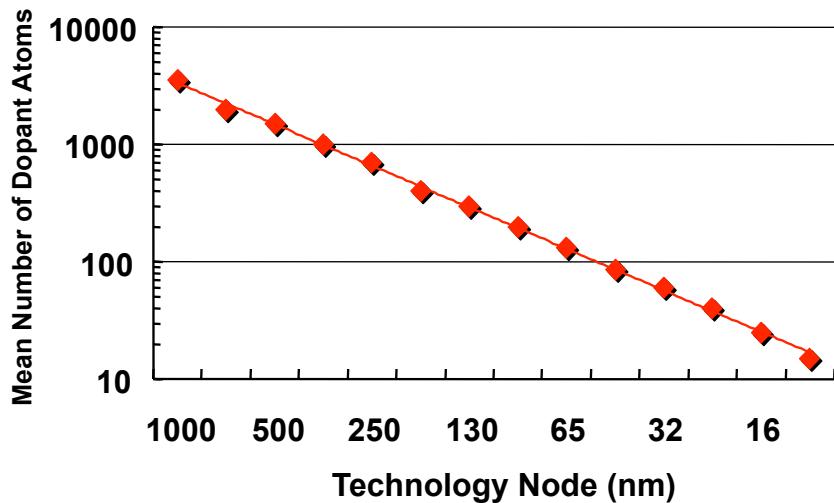
# Today

- Sources of Variation
- Limits of Worst Case
- Optimization for Parametric Yield
- Statistical Analysis



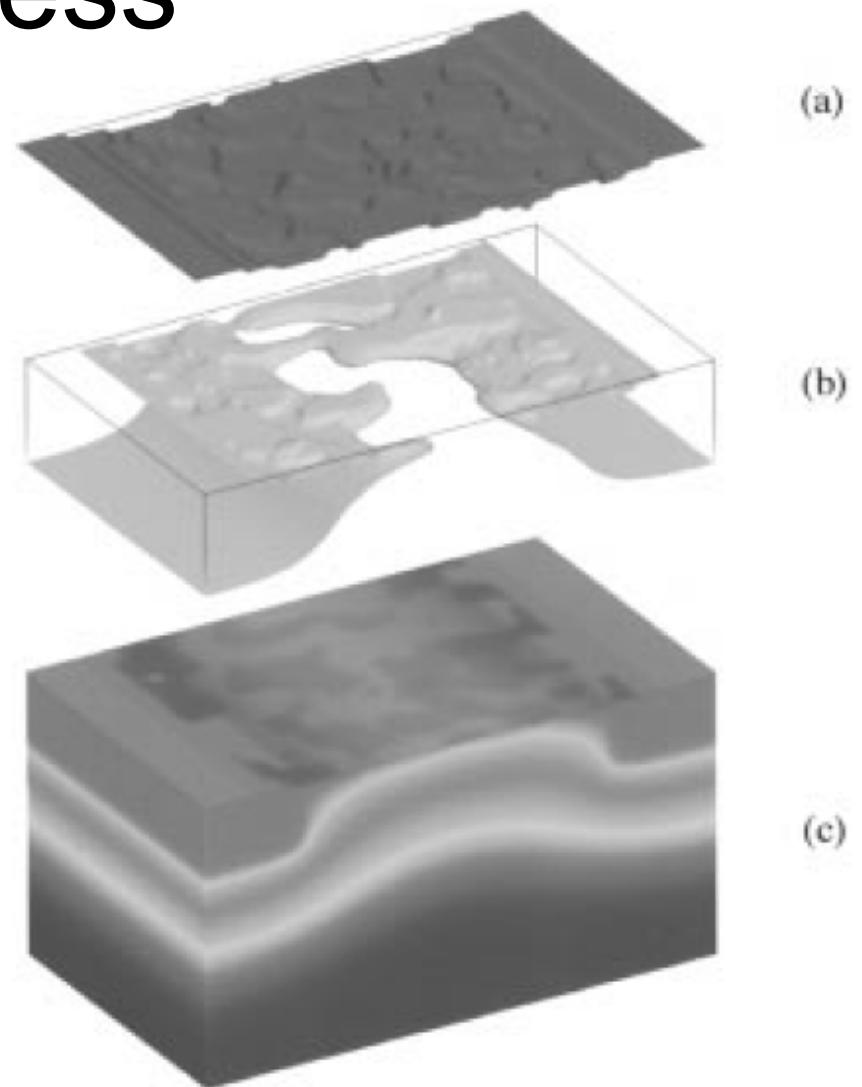
# Central Problem

- As our devices approach the atomic scale, we must deal with statistical effects governing the placement and behavior of individual atoms and electrons.



- Transistor critical dimensions
  - Atomic discreteness
  - Subwavelength litho
  - Etch/polish rates
  - Focus
- Number of dopants
- Dopant Placement

# Oxide Thickness

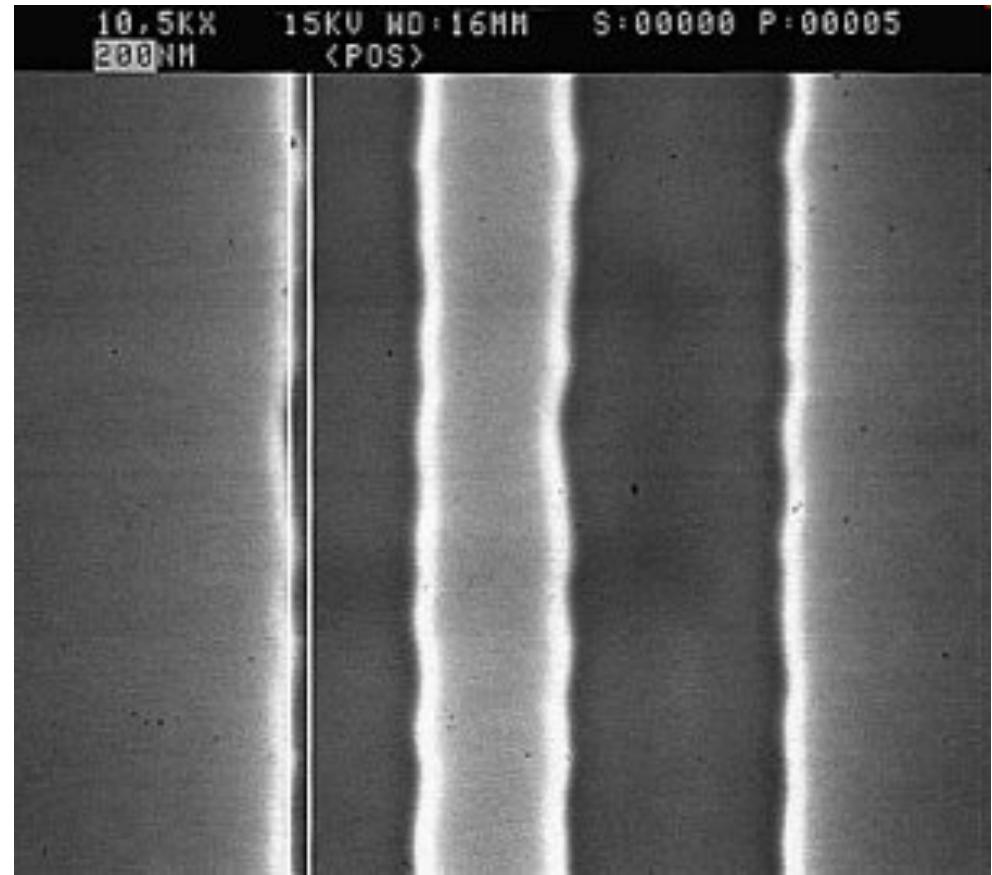


[Asenov et al. TRED 2002]

Fig. 1. (a) Typical profile of the random Si/SiO<sub>2</sub> interface in a  $30 \times 30 \text{ nm}^2$  MOSFET, followed by (b) an equiconcentration contour obtained from DG simulations, and (c) the potential distribution.

# Line Edge Roughness

- $1.2\mu\text{m}$  and  
 $2.4\mu\text{m}$  lines



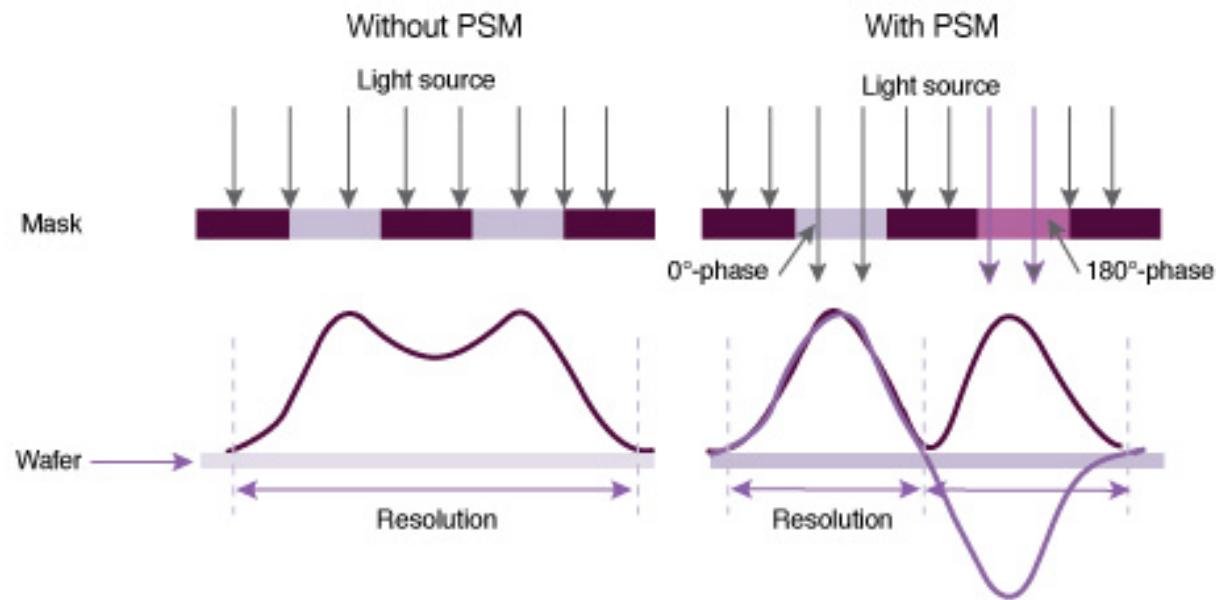
From:

[http://www.microtechweb.com/2d/lw\\_pict.htm](http://www.microtechweb.com/2d/lw_pict.htm)

# Light

- What is wavelength of visible light?

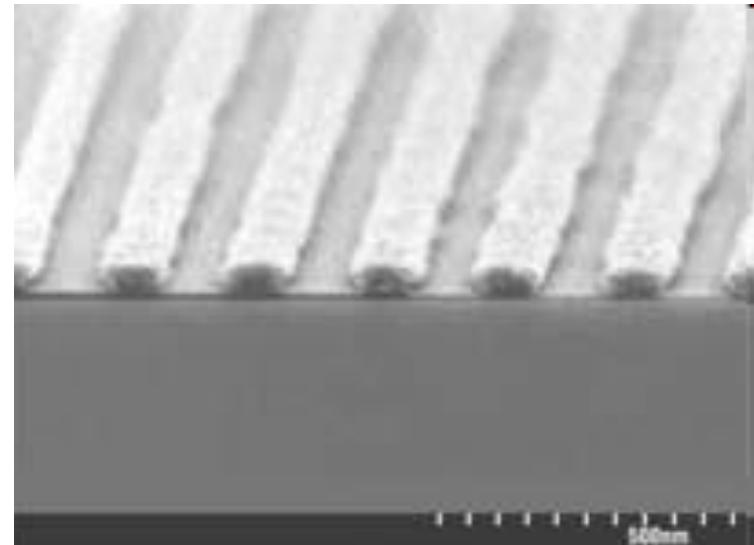
# Phase Shift Masking



Source

<http://www.synopsys.com/Tools/Manufacturing/MaskSynthesis/PSMCreate/Pages/default.aspx>

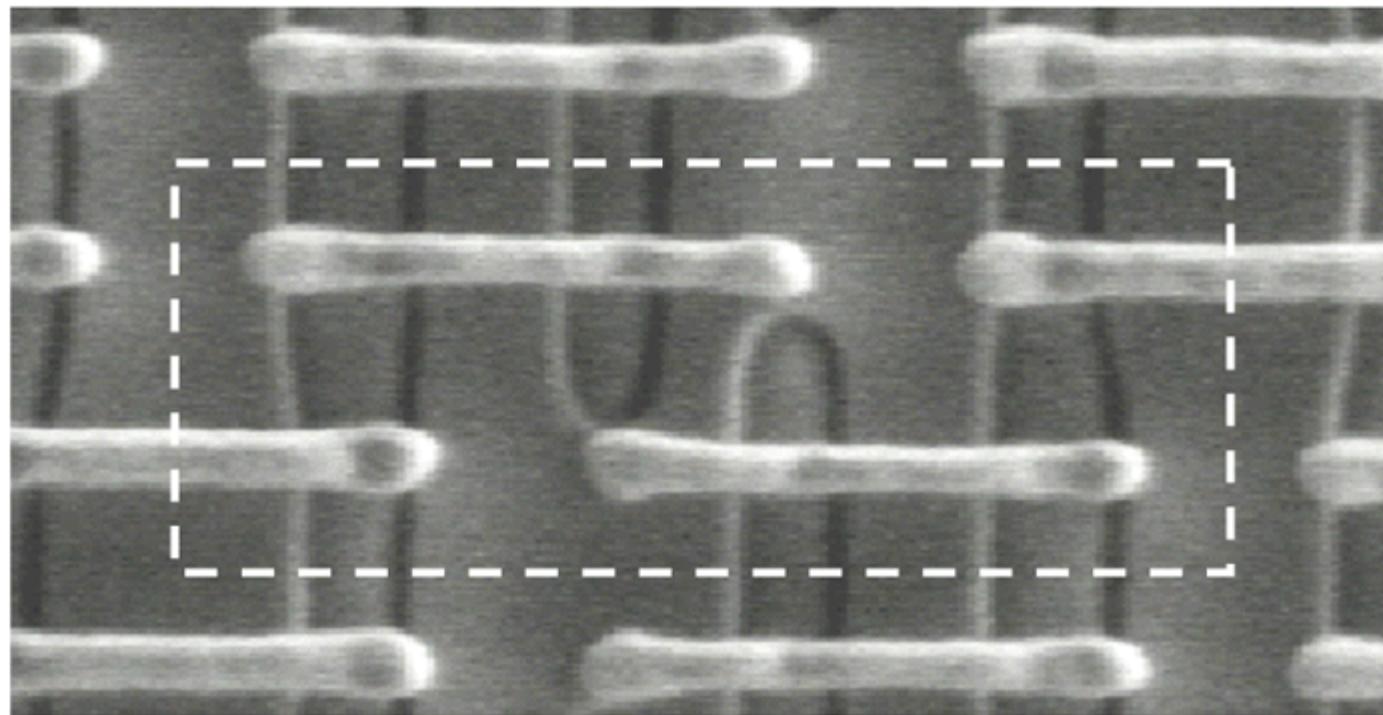
# Line Edges (PSM)



Source:

[http://www.solid-state.com/display\\_article/122066/5/none/none/Feat/Developments-in-materials-for-157nm-photoresists](http://www.solid-state.com/display_article/122066/5/none/none/Feat/Developments-in-materials-for-157nm-photoresists)

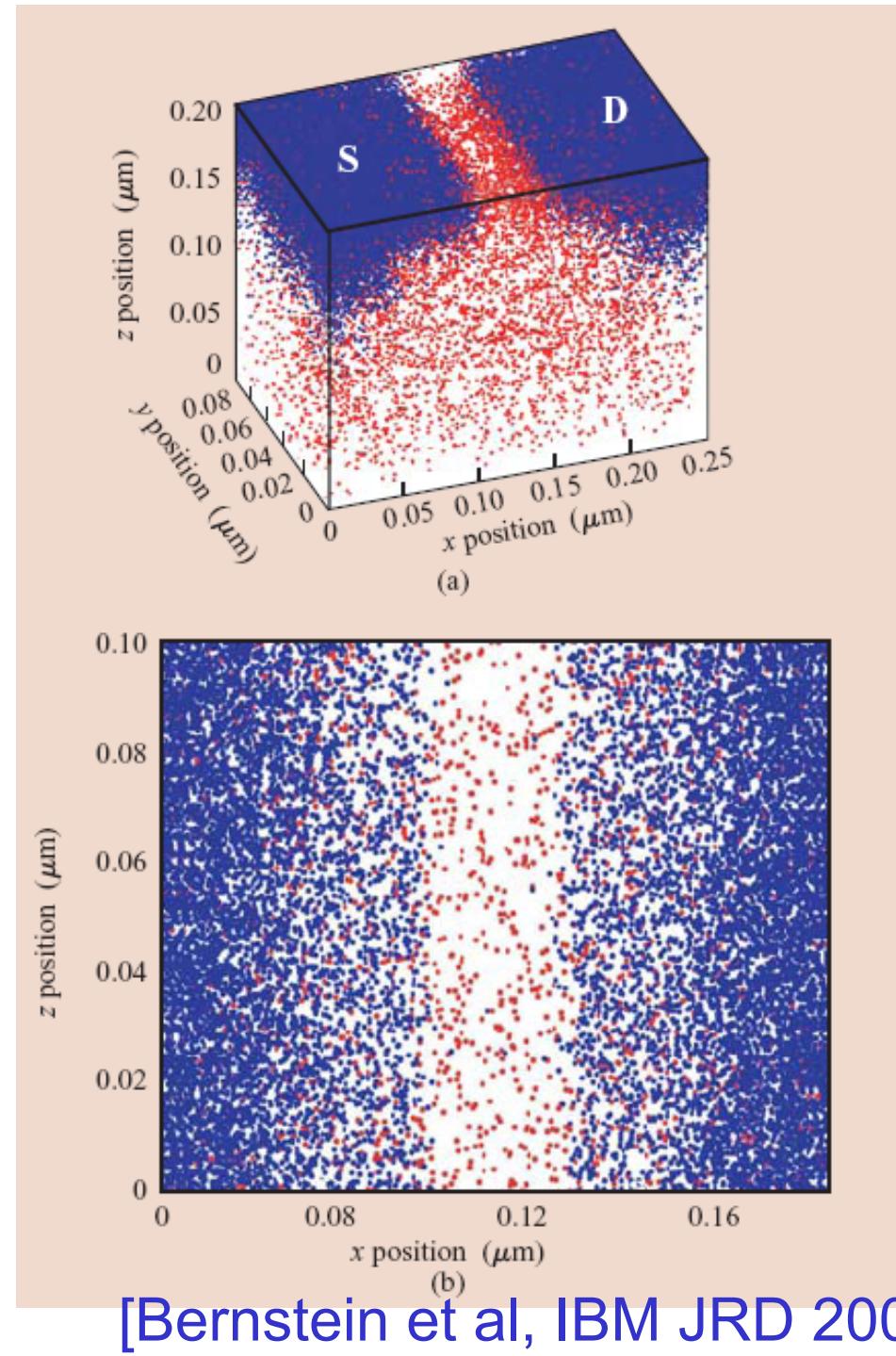
# Intel 65nm SRAM (PSM)



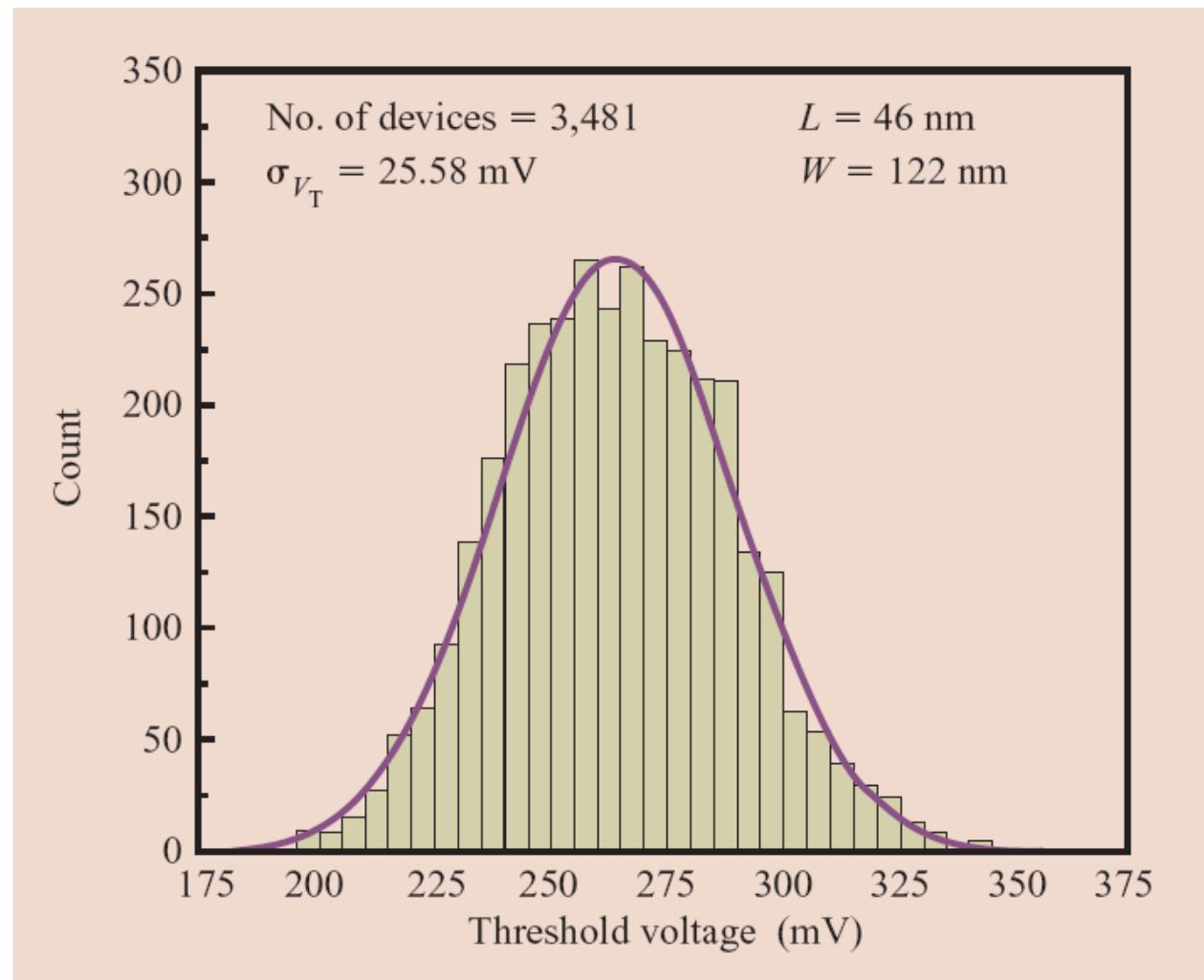
Source:

[http://www.intel.com/technology/itj/2008/v12i2/5-design/figures/Figure\\_5\\_lg.gif](http://www.intel.com/technology/itj/2008/v12i2/5-design/figures/Figure_5_lg.gif) 10  
Penn ESE535 Spring 2013 -- DeHon

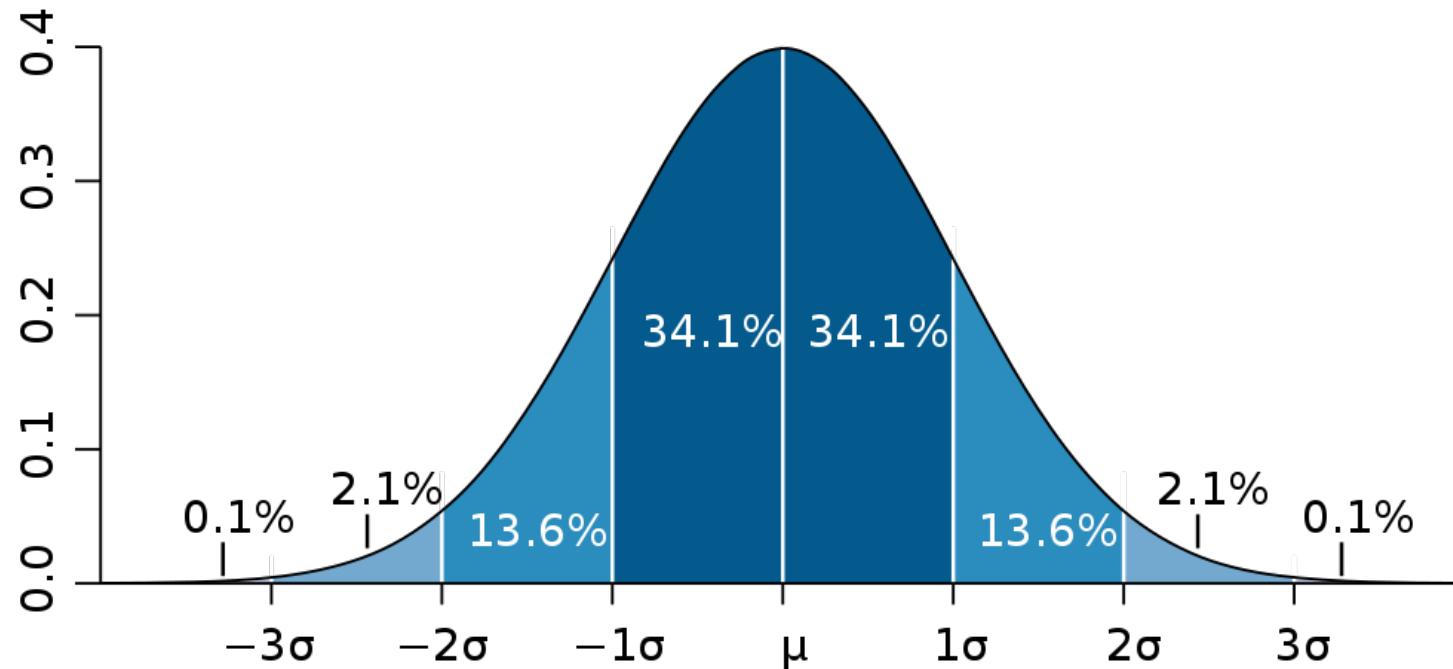
# Statistical Dopant Placement



# $V_{th}$ Variability @ 65nm



# Gaussian Distribution



From: [http://en.wikipedia.org/wiki/File:Standard\\_deviation\\_diagram.svg](http://en.wikipedia.org/wiki/File:Standard_deviation_diagram.svg)

# ITRS 2011 Variation ( $3\sigma$ )

Table DESN10 Design for Manufacturability Technology Requirements

Year of Production	2011	2012	2013	2014	2015	2016	2017	2018	2019	2020	2021	2022	2023	2024	2025	2026
Normalized mask cost from public and IDM data	1.0	1.3	1.7	2.2	2.8	3.7	4.9	6.4	8.4	11.0	14.4	18.8	24.6	32.1	?	?
% $V_{dd}$ variability: % variability seen in on-chip circuits	10%	10%	10%	10%	10%	10%	10%	10%	10%	10%	10%	10%	10%	10%	10%	10%
% $V_{th}$ variability: doping variability impact on $V_{th}$ , (minimum size devices, memory)	40%	40%	40%	45%	45%	50%	50%	55%	55%	60%	60%	65%	65%	70%	70%	75%
% $V_{th}$ variability: includes all sources	42%	42%	42%	47%	47%	53%	53%	58%	58%	63%	63%	68%	68%	74%	74%	79%
% $V_{th}$ variability: typical size logic devices, all sources	20%	20%	20%	23%	23%	25%	25%	28%	28%	30%	30%	33%	33%	35%	35%	38%
% CD variability	12%	12%	12%	12%	12%	12%	12%	12%	12%	12%	12%	12%	12%	12%	12%	12%
% circuit performance variability circuit comprising gates and wires	42%	42%	42%	45%	45%	47%	47%	50%	50%	52%	52%	55%	55%	57%	57%	60%
% circuit total power variability circuit comprising gates and wires	51%	51%	51%	55%	55%	59%	59%	63%	63%	68%	68%	72%	72%	77%	77%	81%
% circuit leakage power variability circuit comprising gates and wires	126%	126%	126%	129%	129%	132%	132%	135%	135%	138%	138%	141%	141%	145%	145%	148%

# Example: $V_{th}$

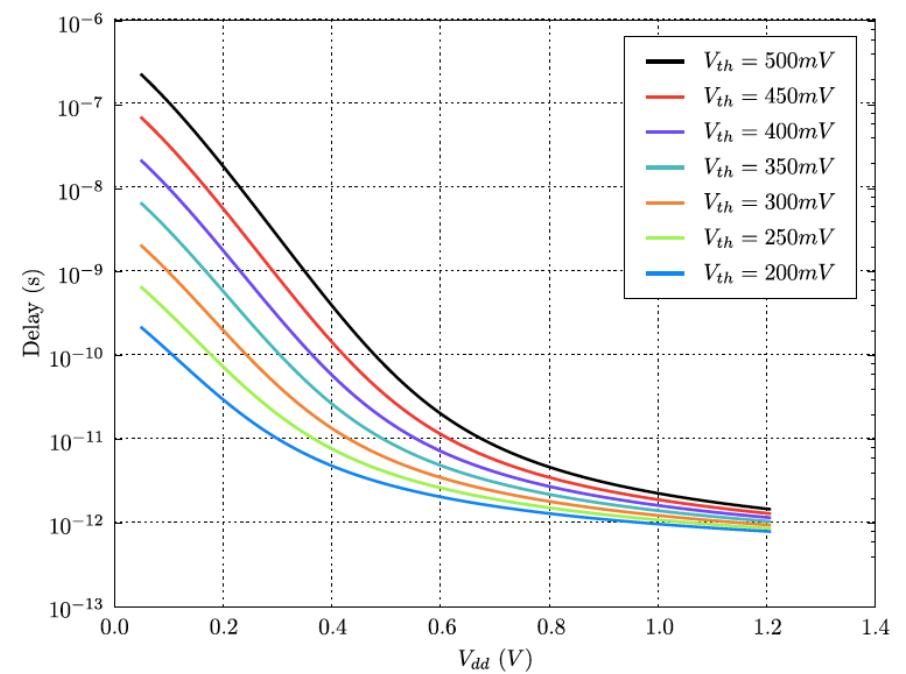
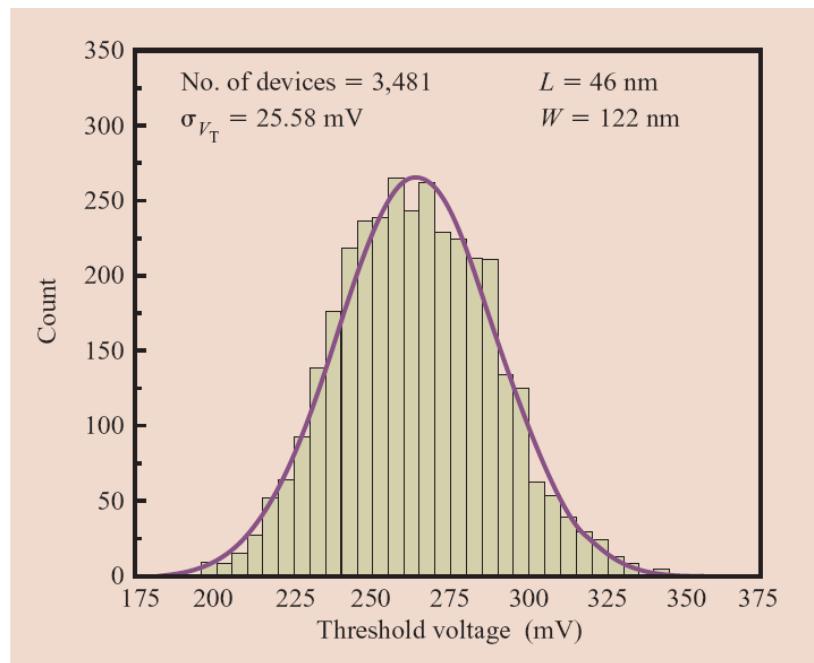
- Many physical effects impact  $V_{th}$ 
  - Doping, dimensions, roughness
- Behavior highly dependent on  $V_{th}$

$$I_{DS} = \frac{\mu_n C_{OX}}{2} \left( \frac{W}{L} \right) \left[ (V_{GS} - V_{th})^2 \right]$$

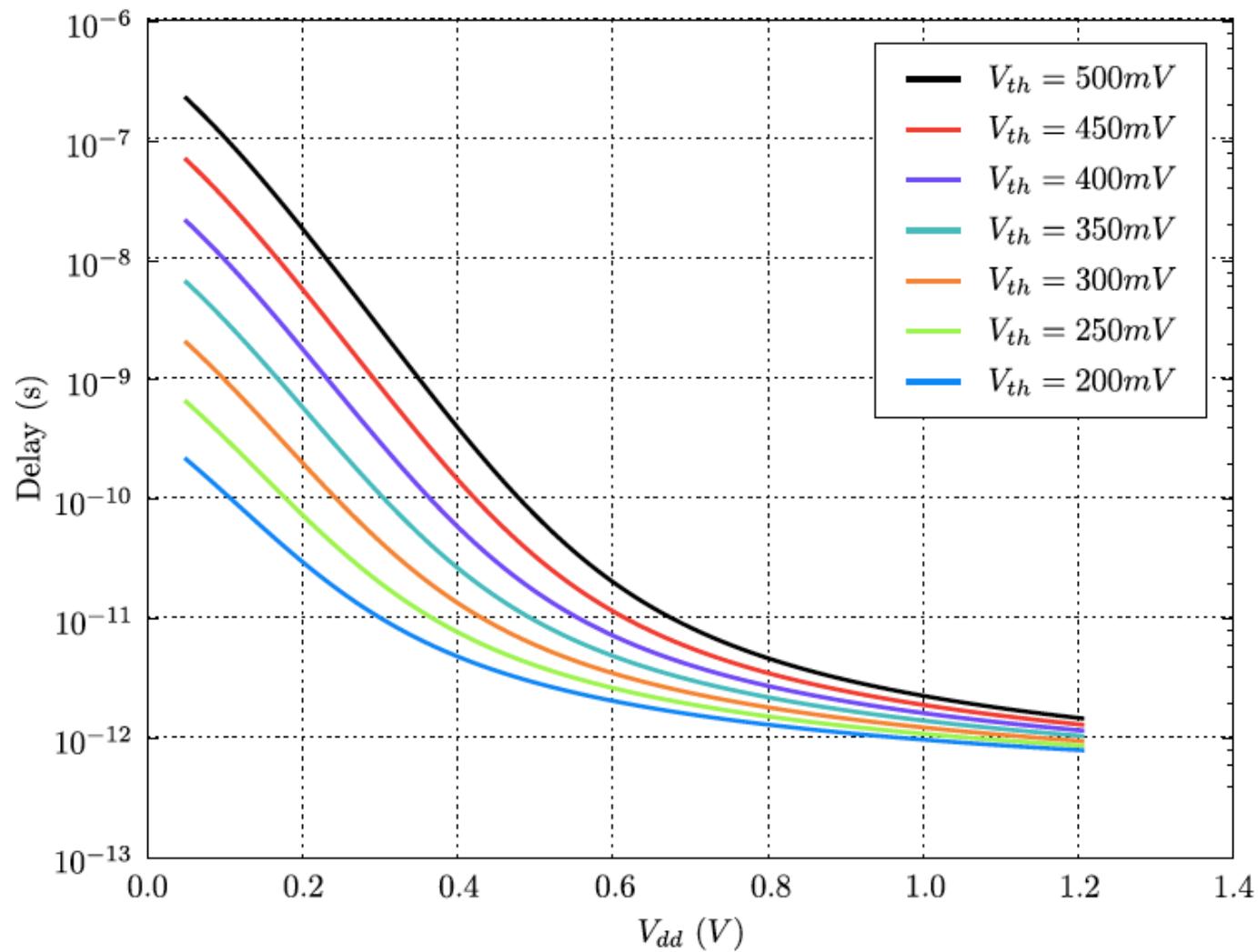
$$I_{DS} = I_S \left( \frac{W}{L} \right) e^{\left( \frac{V_{GS} - V_{th}}{nkT/q} \right)} \left( 1 - e^{-\left( \frac{V_{DS}}{kT/q} \right)} \right) \left( 1 + \lambda V_{DS} \right)$$

# Impact Performance

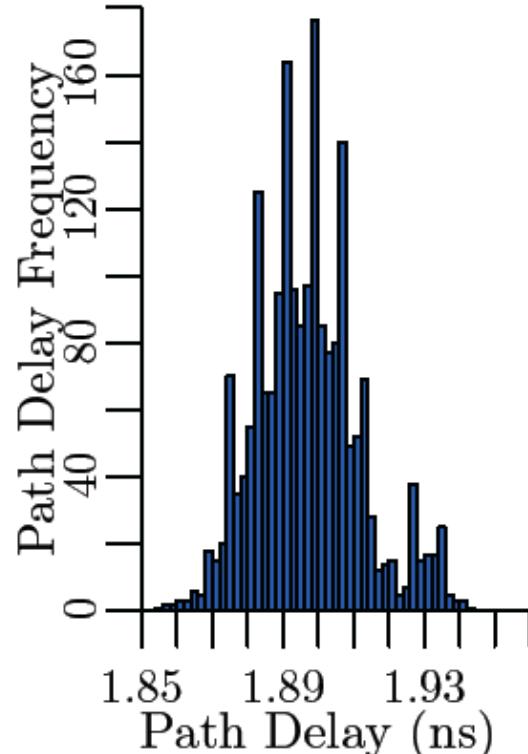
- $V_{th} \rightarrow I_{ds} \rightarrow \text{Delay } (C_{\text{load}}/I_{ds})$



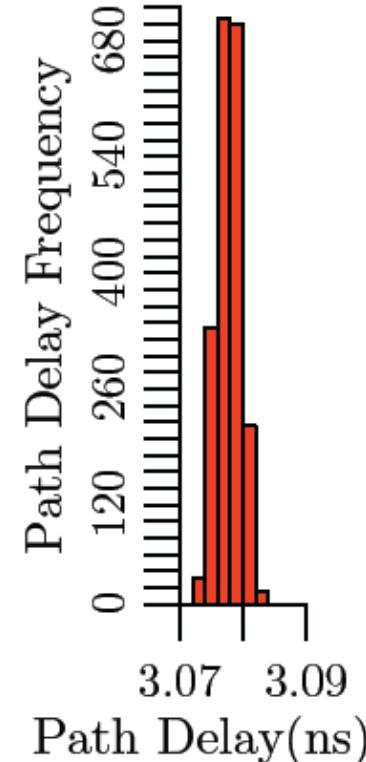
# Impact of $V_{th}$ Variation



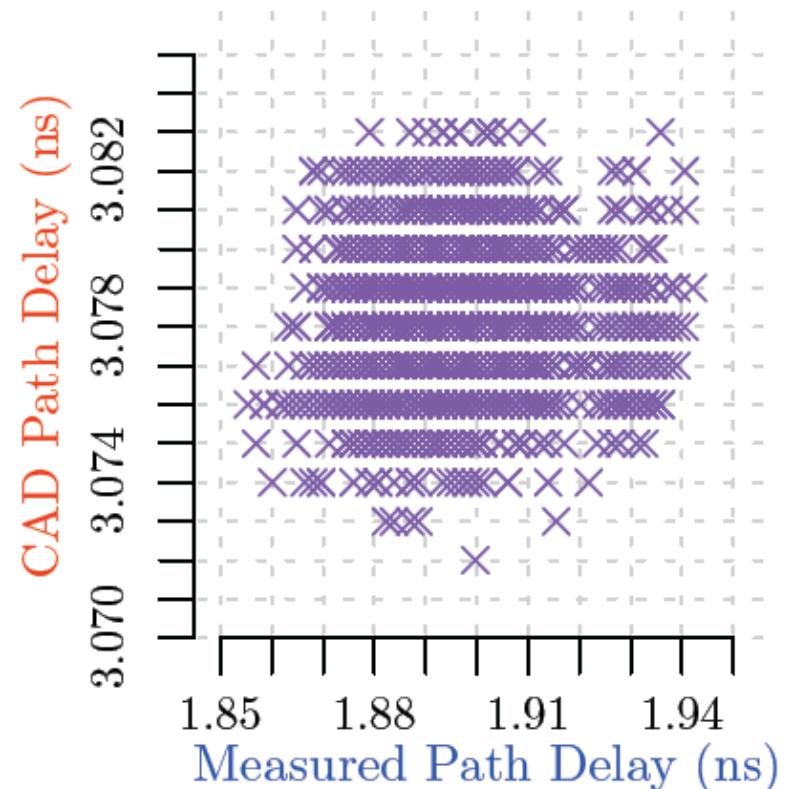
# Variation in Current FPGAs



(a) Measured Delay



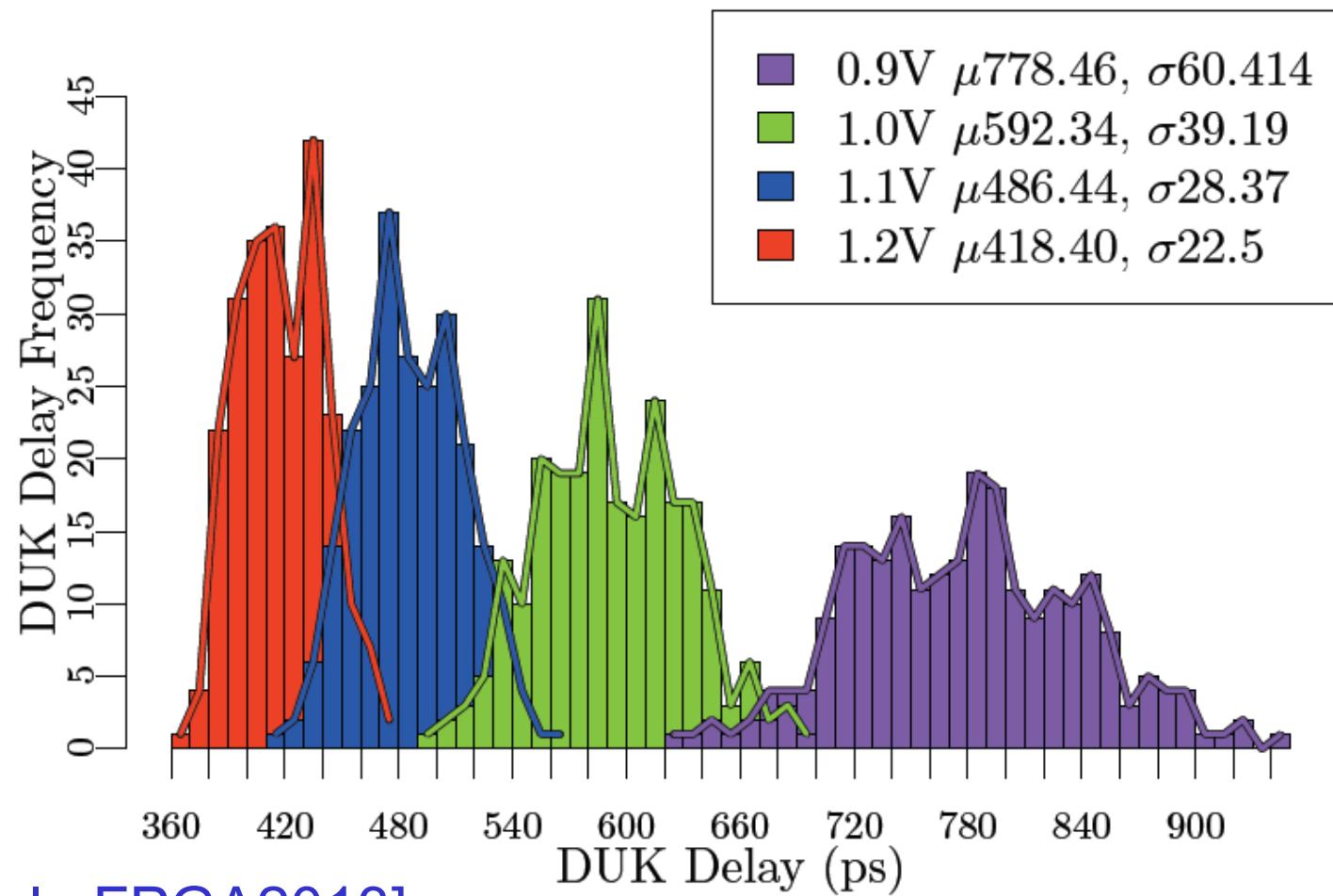
(b) CAD Delay



(c) Correlation

[Gojman et al., FPGA2013]

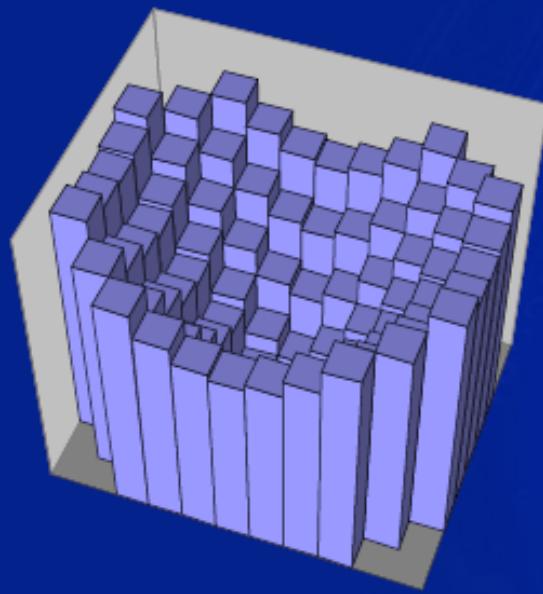
# Reduce Vdd (Cyclone IV 60nm LP)



[Gojman et al., FPGA2013]

# Scale of Variations

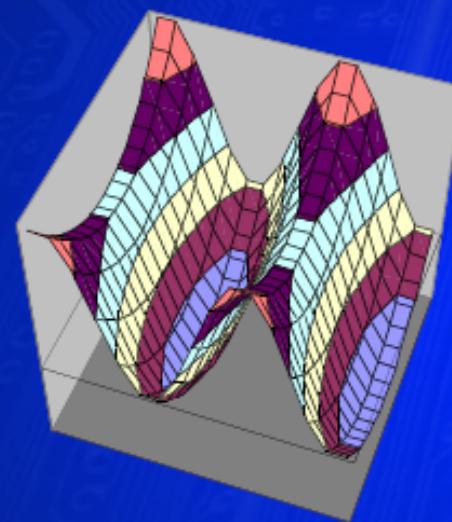
## Die-to-Die (D2D) Variations



**Wafer Scale**

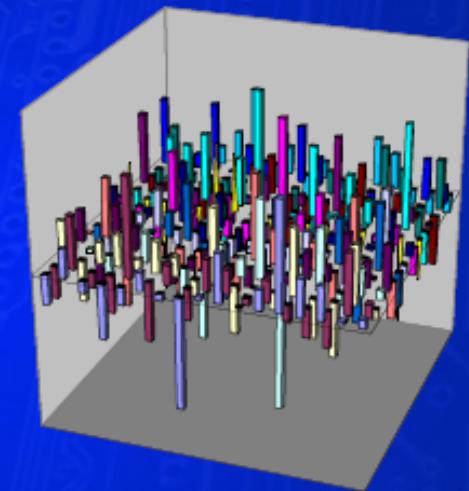
## Within-Die (WID) Variations

### Systematic



**Die Scale**

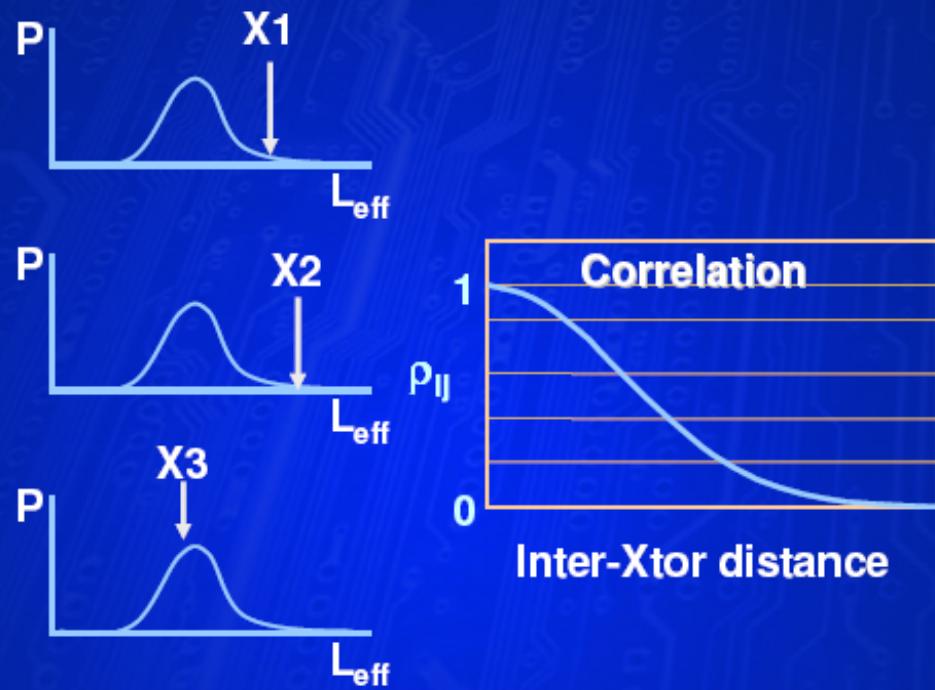
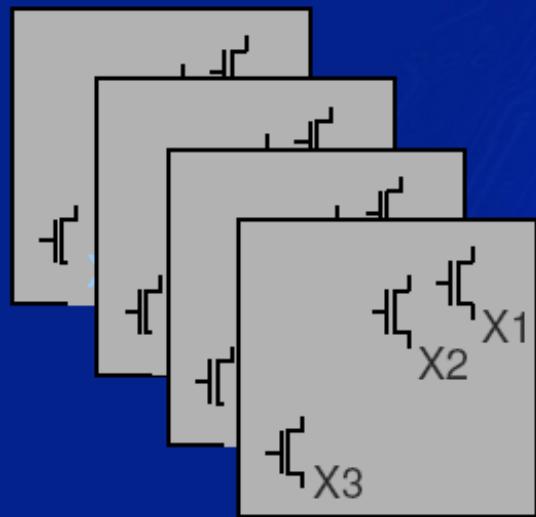
### (Uncorrelated) Random



**Feature Scale**

Source: Noel Menezes, Intel ISPD2007

# Nature of correlated variation



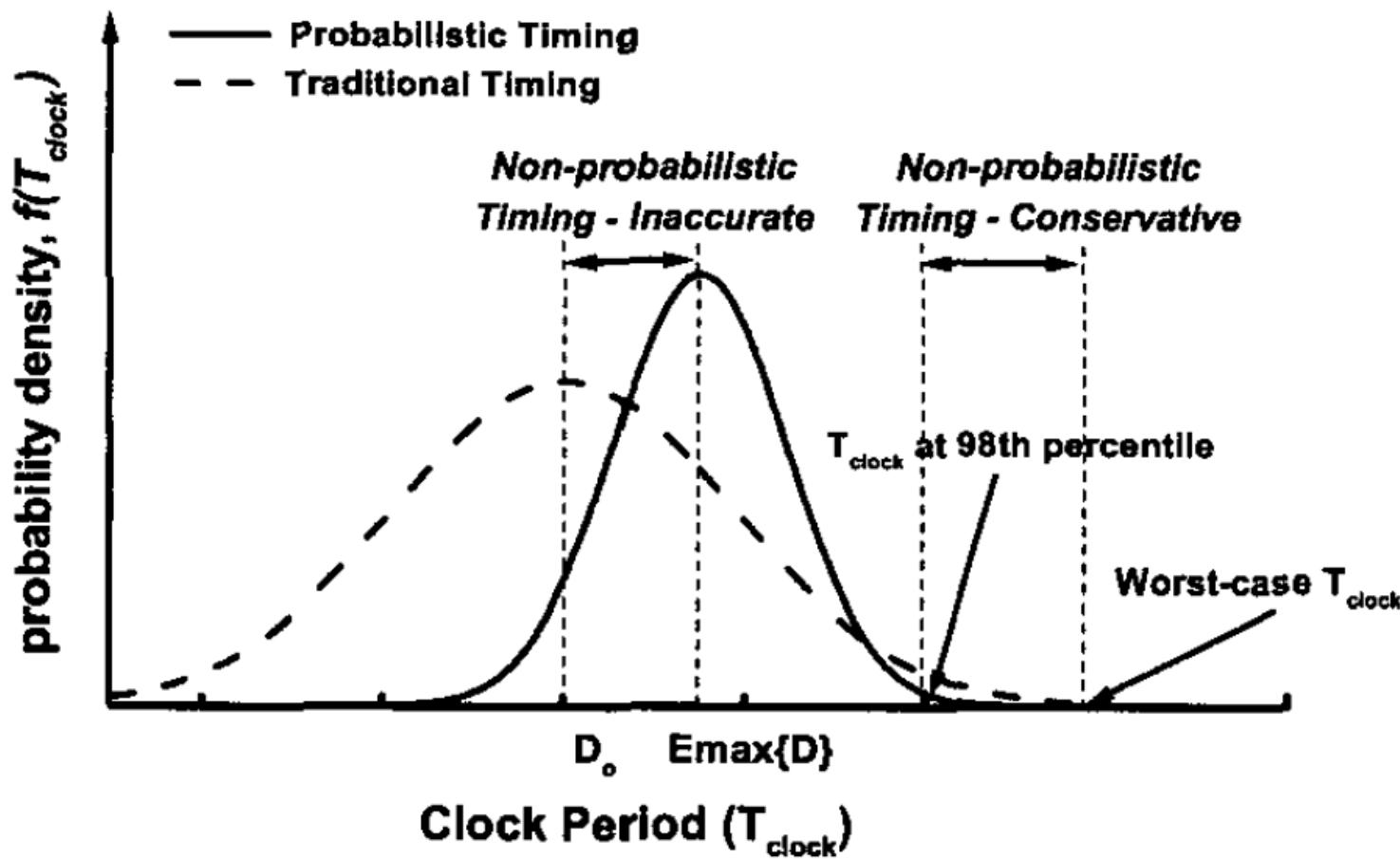
- CDs of transistors that are close track
  - Tracking diminishes with distance

Source: Noel Menezes, Intel ISPD2007

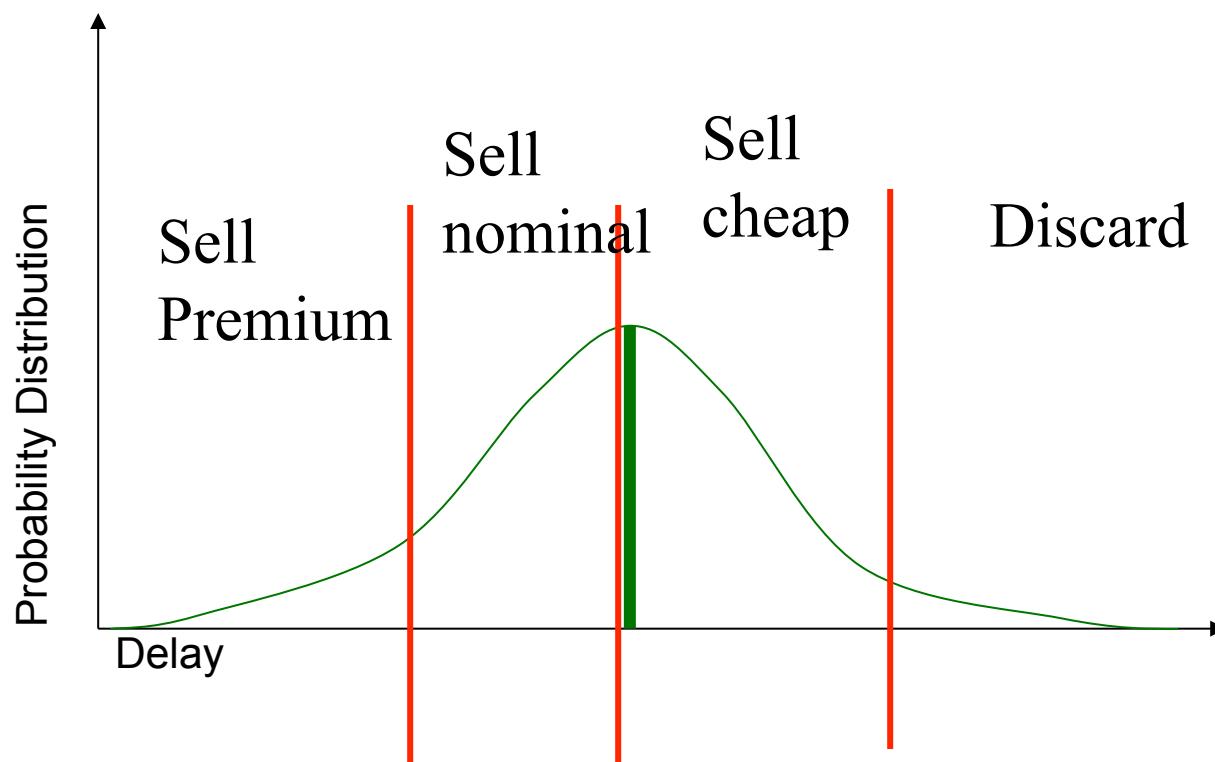
# Old Way

- Characterize gates by corner cases
  - Fast, nominal, slow
- Add up corners to estimate range
- Preclass:
  - Slow corner: 1.1
  - Nominal: 1.0
  - Fast corner: 0.9

# Corners Misleading

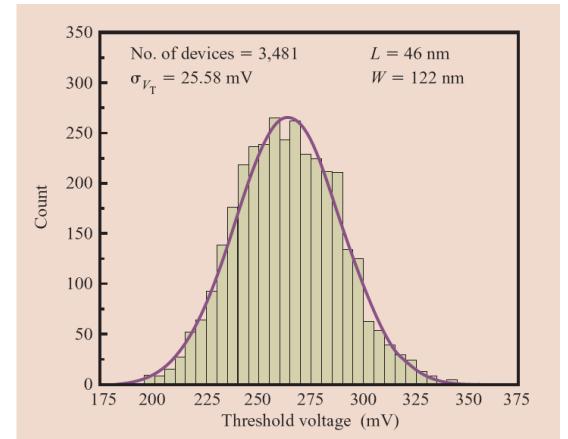
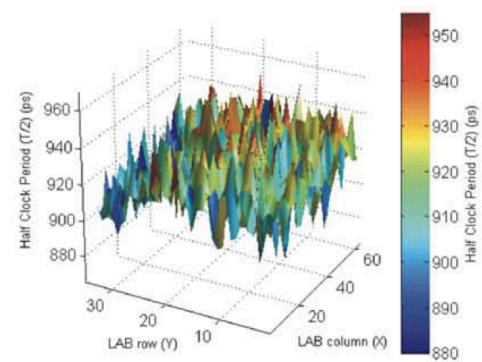
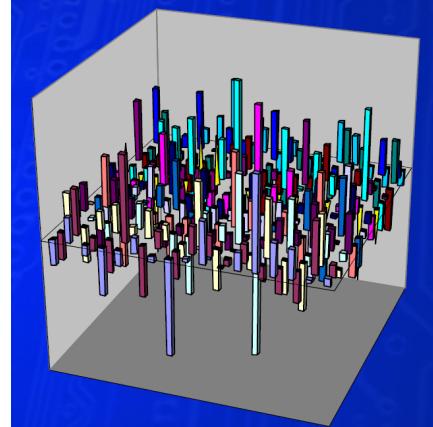


# Parameteric Yield



# Phenomena 1: Path Averaging

- $T_{\text{path}} = t_0 + t_1 + t_2 + t_3 + \dots + t_{(d-1)}$
- $T_i$  – iid random variables
  - Mean  $\tau$
  - Variance  $\sigma$
- $T_{\text{path}}$ 
  - Mean  $d \times \tau$
  - Variance =  $\sqrt{d} \times \sigma$



# Sequential Paths

- $T_{\text{path}} = t_0 + t_1 + t_2 + t_3 + \dots + t_{(d-1)}$
- $T_{\text{path}}$ 
  - Mean  $d \times \tau$
  - Variance =  $\sqrt{d} \times \sigma$
- 3 sigma delay on path:  $d \times \tau + 3\sqrt{d} \times \sigma$ 
  - Worst case per component would be:  
 $d \times (\tau + 3 \sigma)$
  - Overestimate  $d$  vs.  $\sqrt{d}$

# SSTA vs. Corner Models

- STA with corners predicts 225ps
- SSTA predicts 162ps at  $3\sigma$
- SSTA reduces pessimism by 28%

[Slide composed  
by Nikil Mehta]

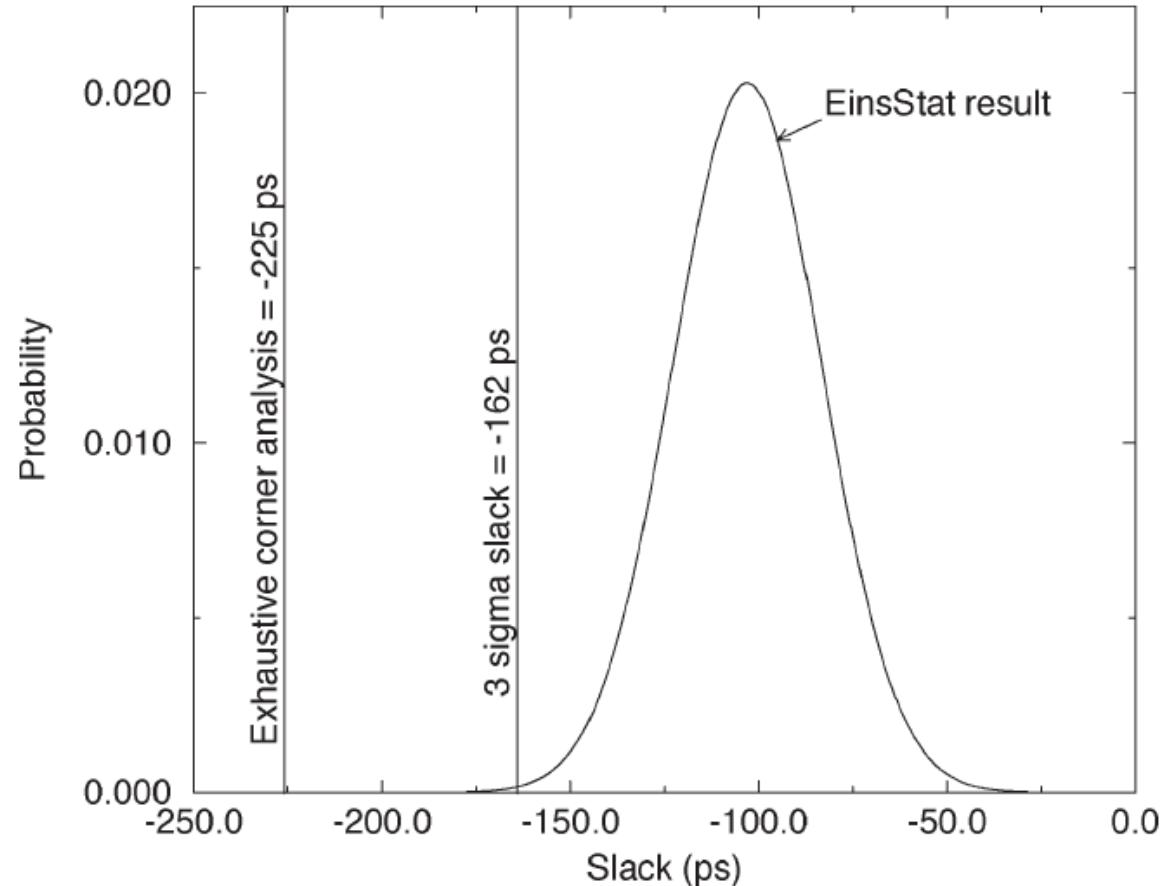
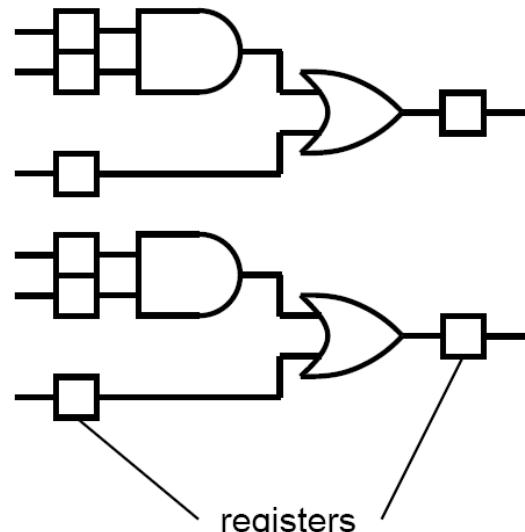


Fig. 11. EinsStat result on industrial ASIC design for early mode slacks.

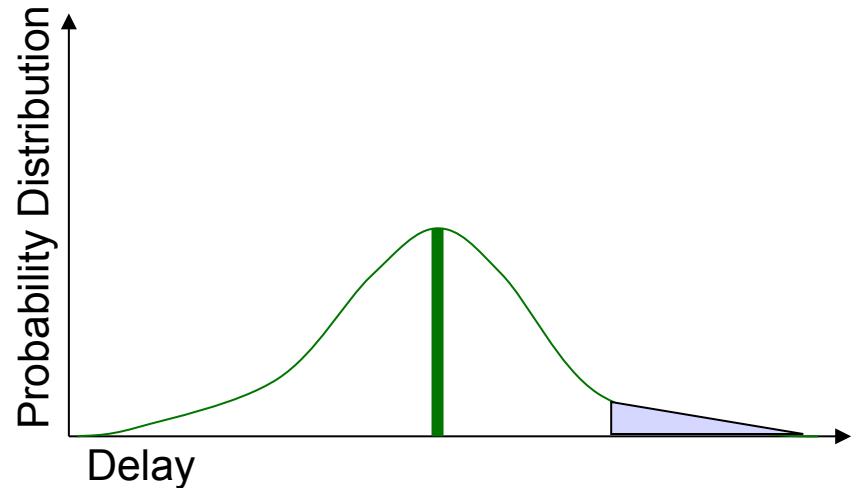
# Phenomena 2: Parallel Paths

- Cycle time limited by slowest path
- $T_{cycle} = \max(T_{p0}, T_{p1}, T_{p2}, \dots, T_{p(n-1)})$
- $P(T_{cycle} < T_0) = P(T_{p0} < T_0) \times P(T_{p1} < T_0) \dots$   
•  $= [P(T_p < T_0)]^n$
- $0.5 = [P(T_p < T_{50})]^n$
- $P(T_p < T_{50}) = (0.5)^{(1/n)}$

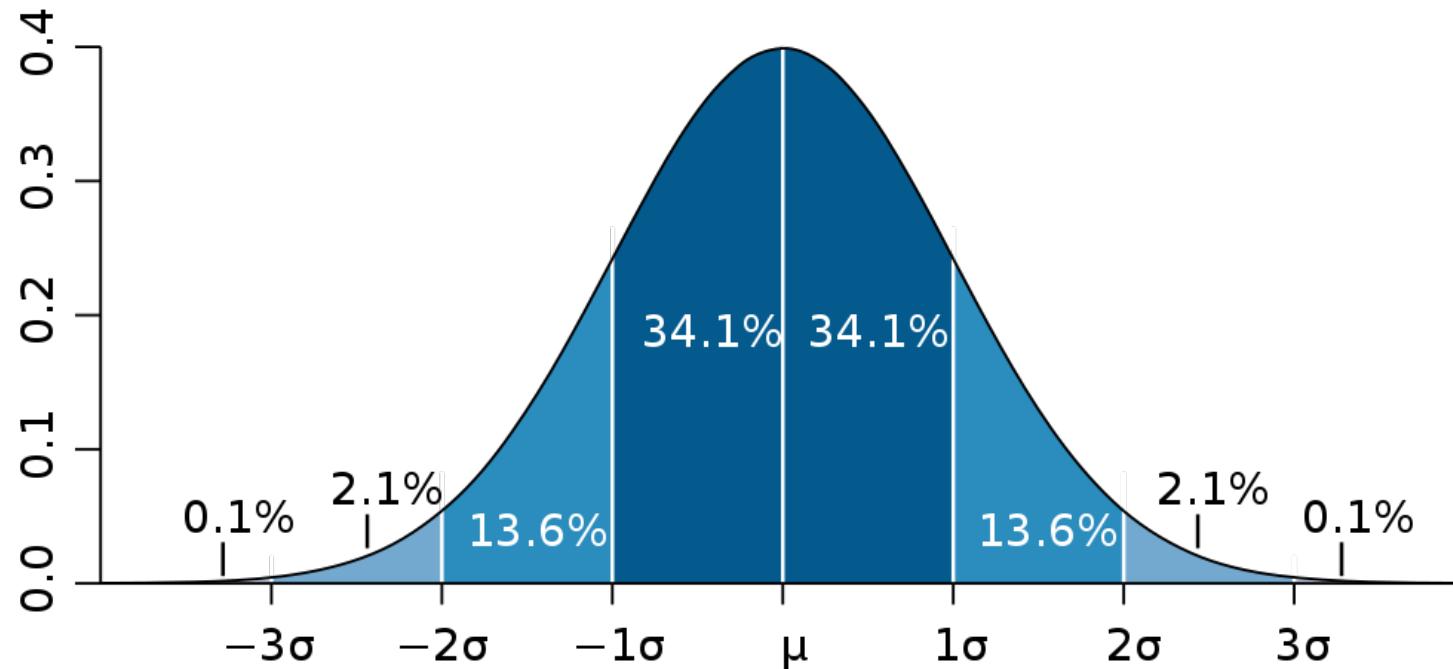


# System Delay

- $P(T_p < T_{50}) = (0.5)^{(1/n)}$ 
  - $N=10^8 \rightarrow 0.999999993$ 
    - $1.7 \times 10^{-9}$
  - $N=10^{10} \rightarrow 0.99999999993$ 
    - $1.7 \times 10^{-11}$



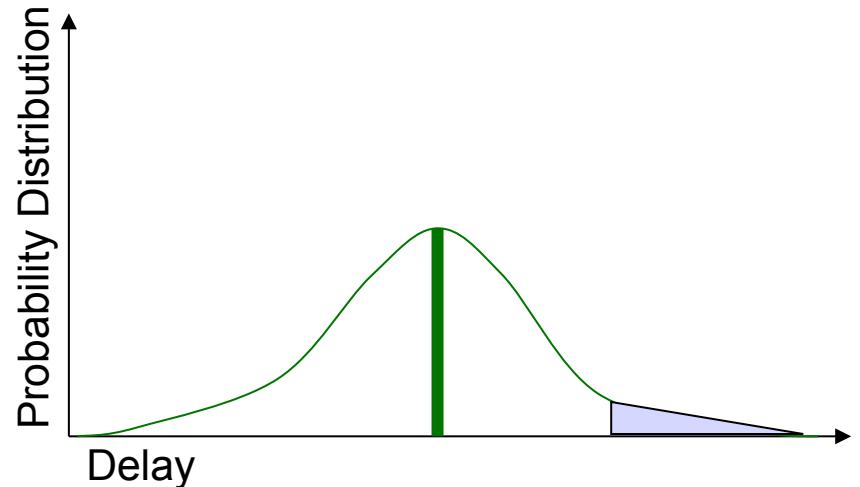
# Gaussian Distribution



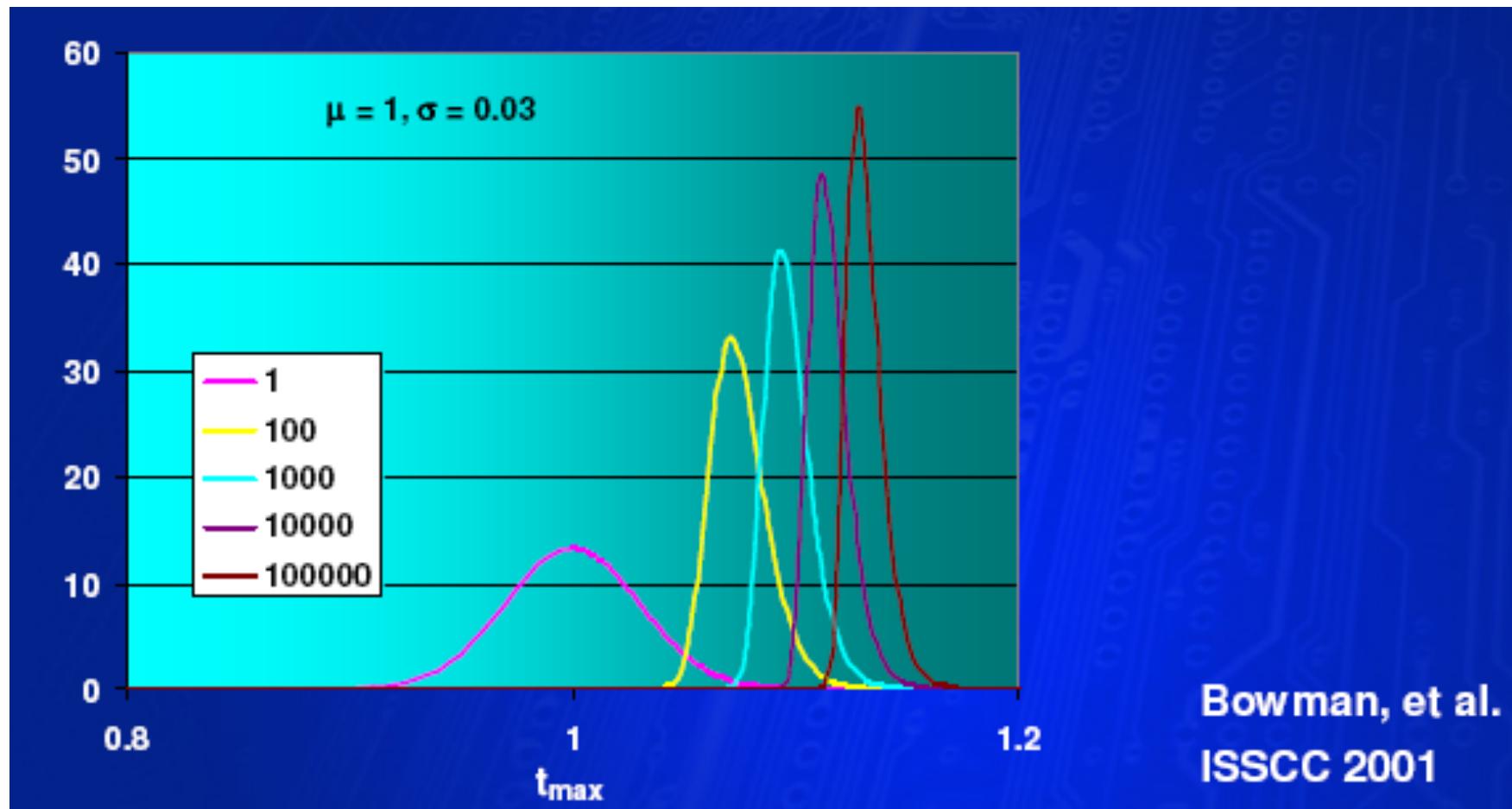
From: [http://en.wikipedia.org/wiki/File:Standard\\_deviation\\_diagram.svg](http://en.wikipedia.org/wiki/File:Standard_deviation_diagram.svg)

# System Delay

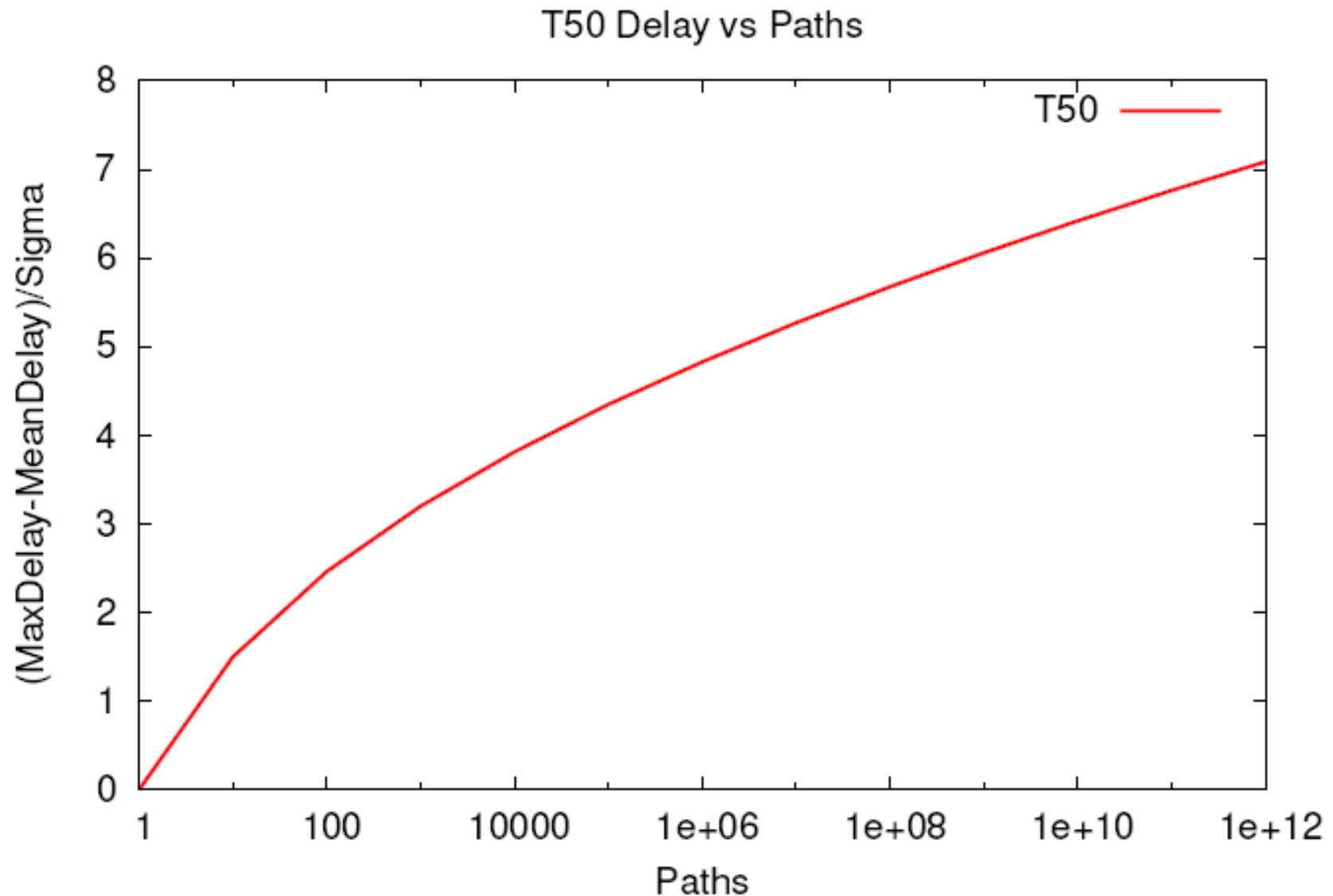
- $P(T_p < T_{50}) = (0.5)^{(1/n)}$ 
  - $N=10^8 \rightarrow 0.999999993$ 
    - $1-7 \times 10^{-9}$
  - $N=10^{10} \rightarrow 0.99999999993$ 
    - $1-7 \times 10^{-11}$
- For 50% yield want
  - 6 to 7  $\sigma$
  - $T_{50} = T_{\text{mean}} + 7\sigma_{\text{path}}$



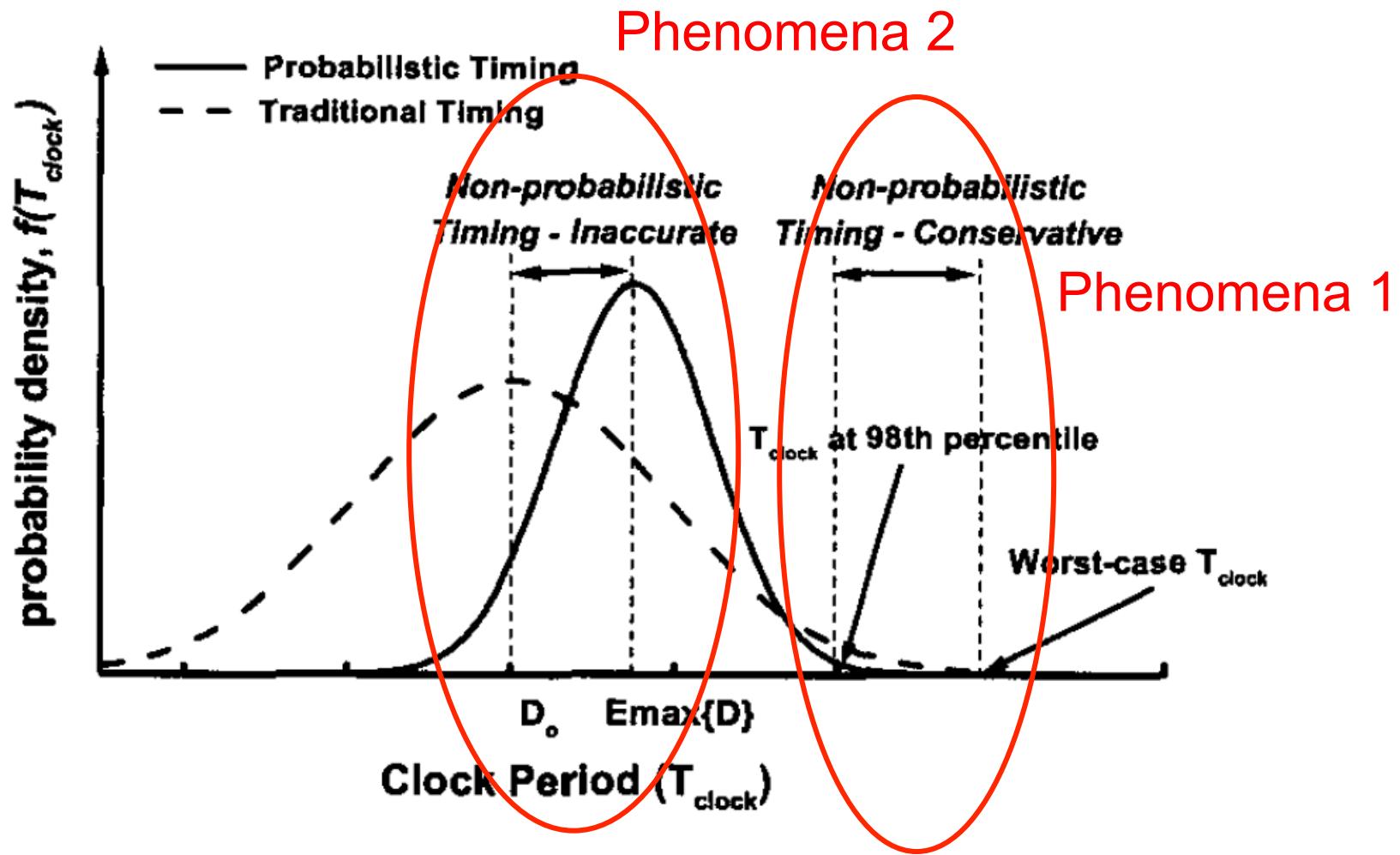
# System Delay



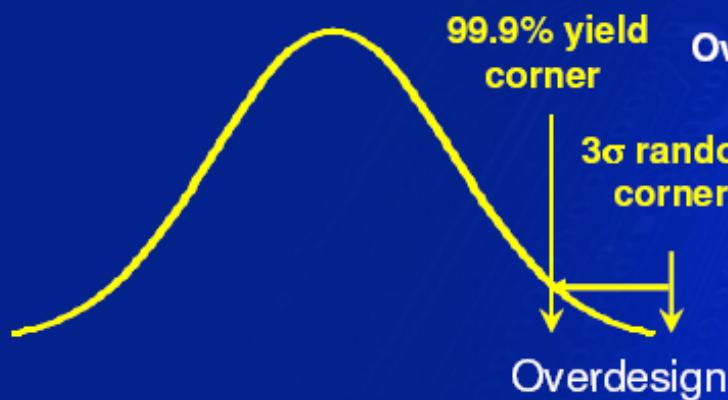
# System Delay



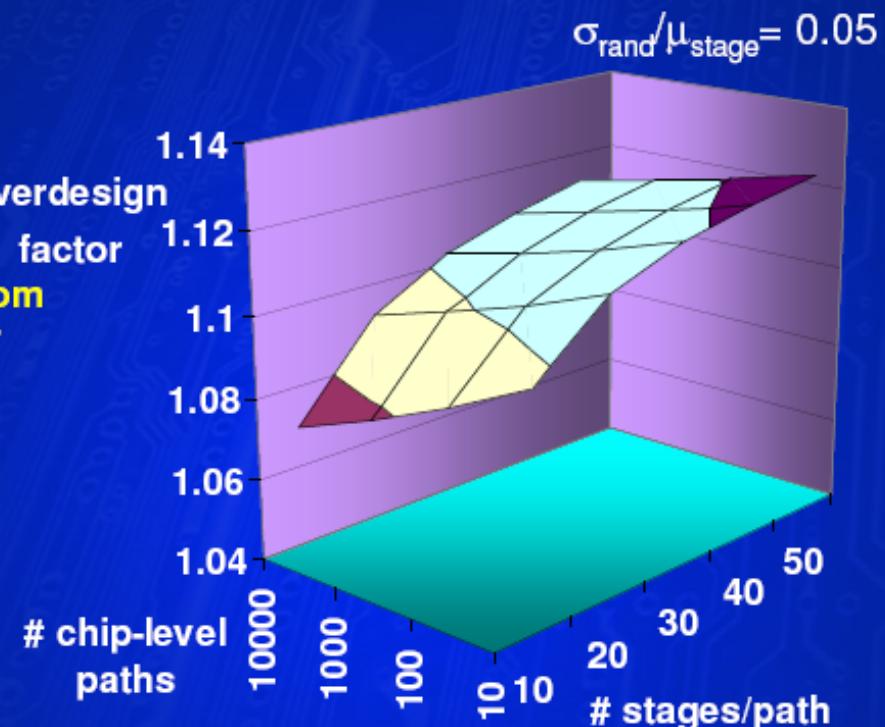
# Corners Misleading



# SSTA gain relative to $3\sigma$ corner analysis: Random



$$gain = \frac{1 + 3\sigma_{rand}}{1 + \frac{\Phi^{-1}\left(Y^{1/N_p}\right)}{\sqrt{n_{cp}}} \sigma_{rand}}$$

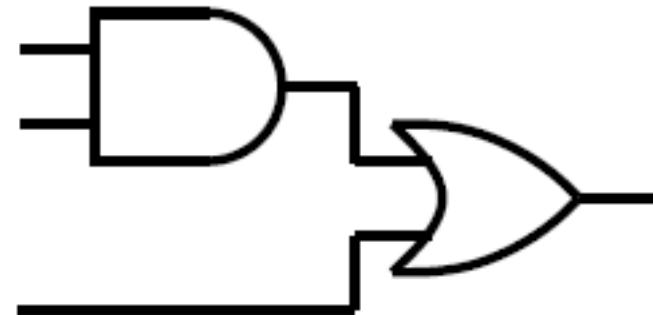
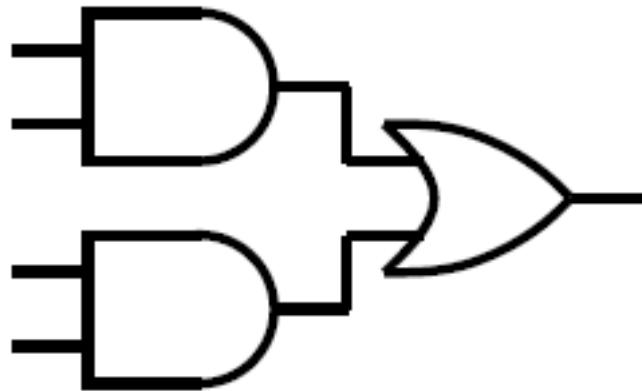


- SSTA provides a potential gain relative to a  $3\sigma$  corner-based STA for purely random variation

Source: Noel Menezes, Intel ISPD2007

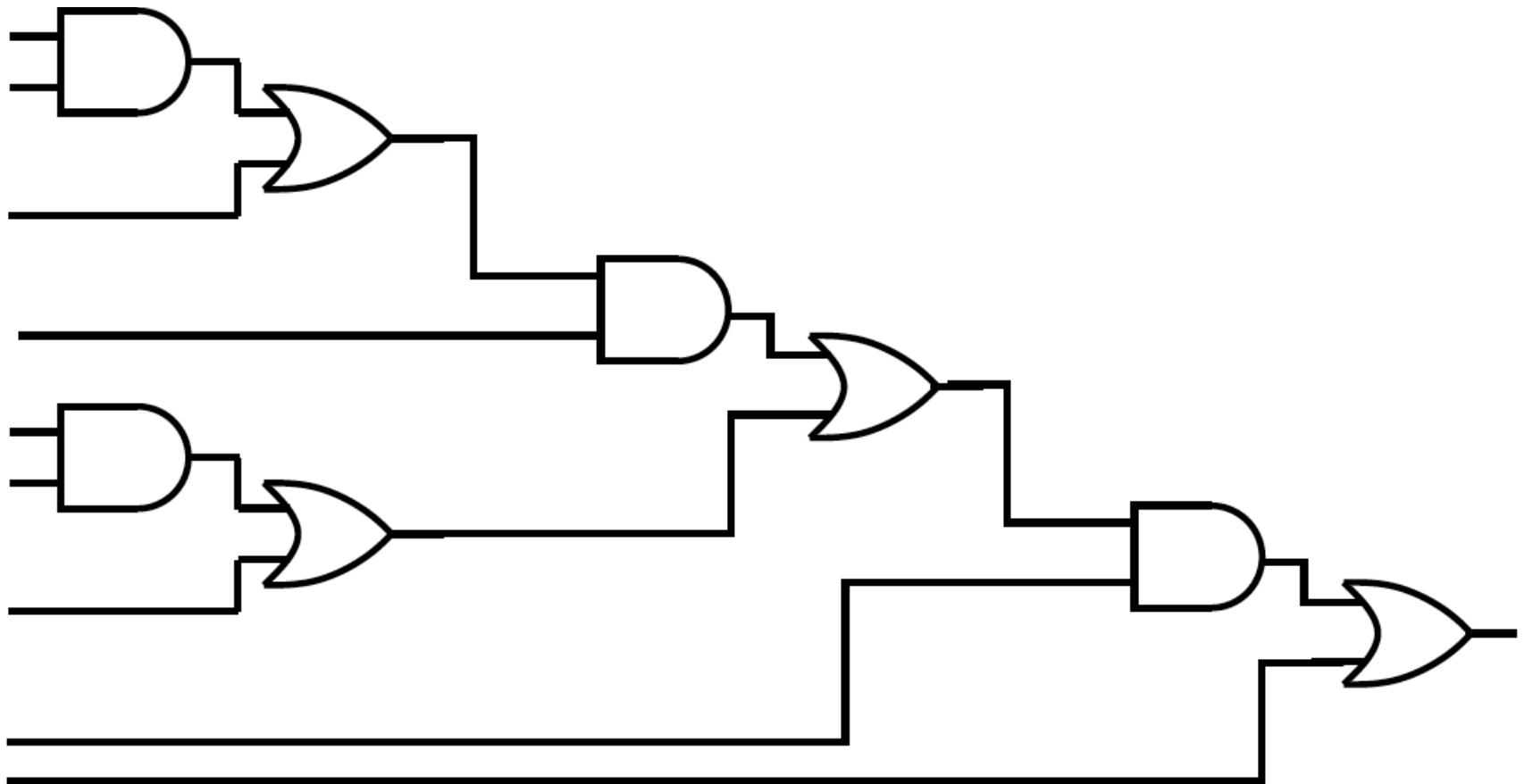
# But does worst-case mislead?

- STA with worst-case says these are equivalent:



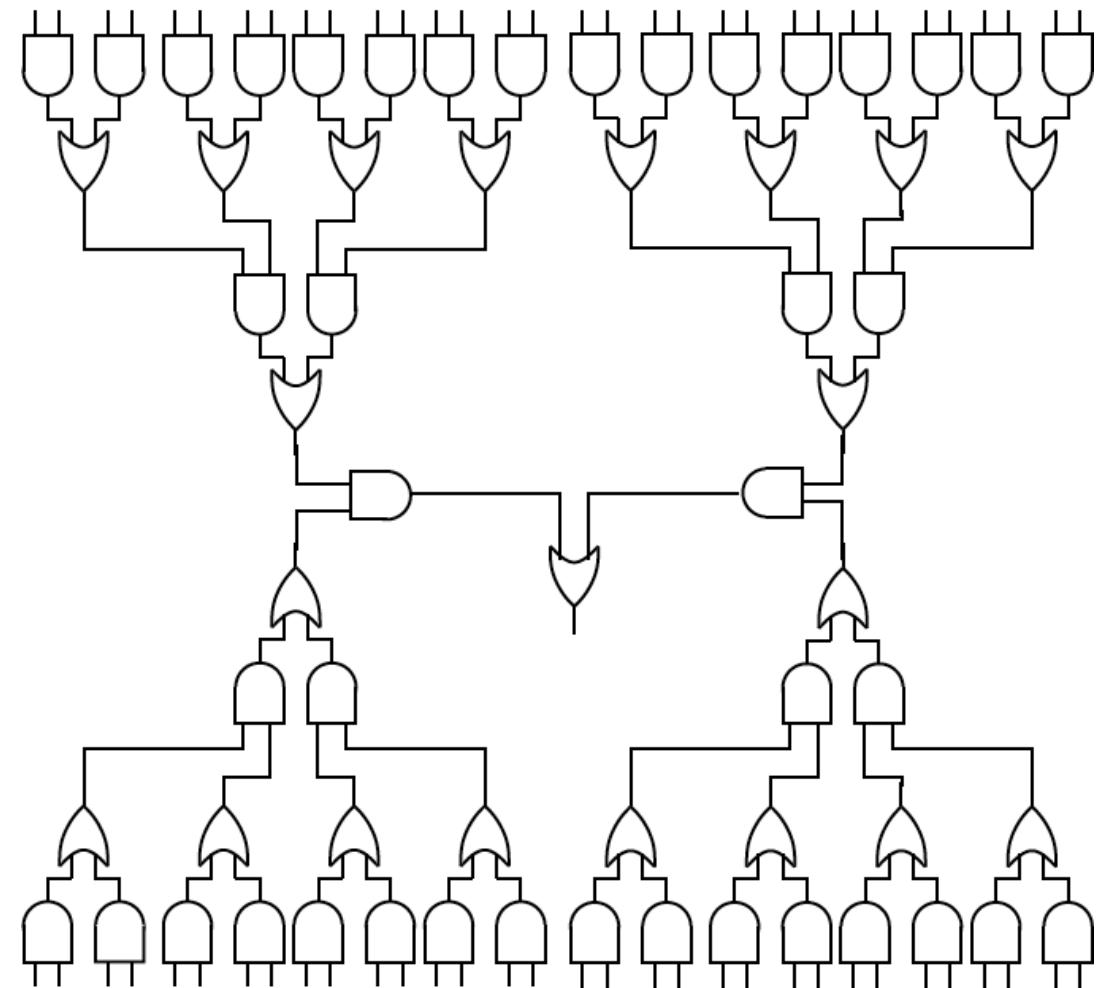
# But does worst-case mislead?

- STA Worst case delay for this?



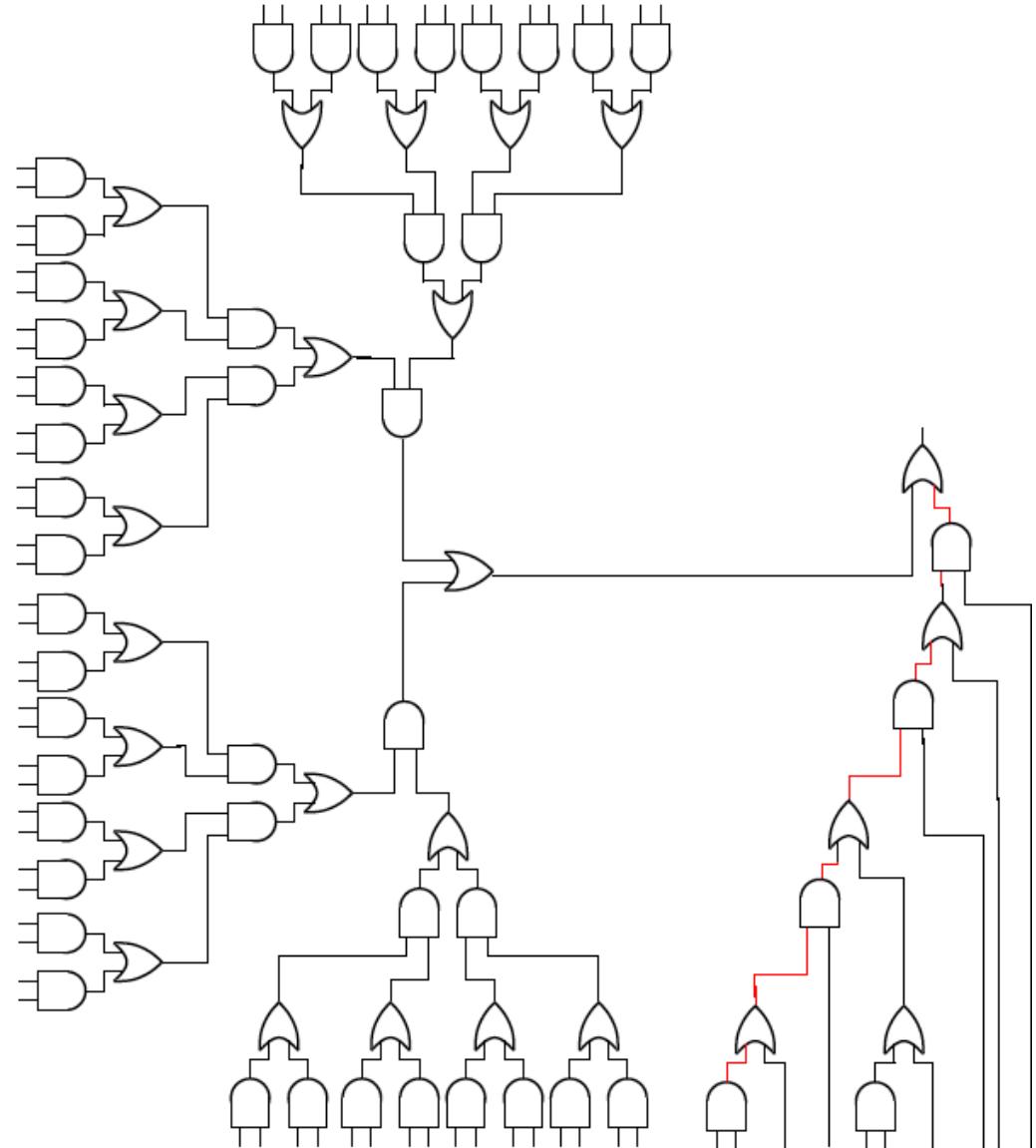
# But does worst-case mislead?

- STA Worst case delay for this?

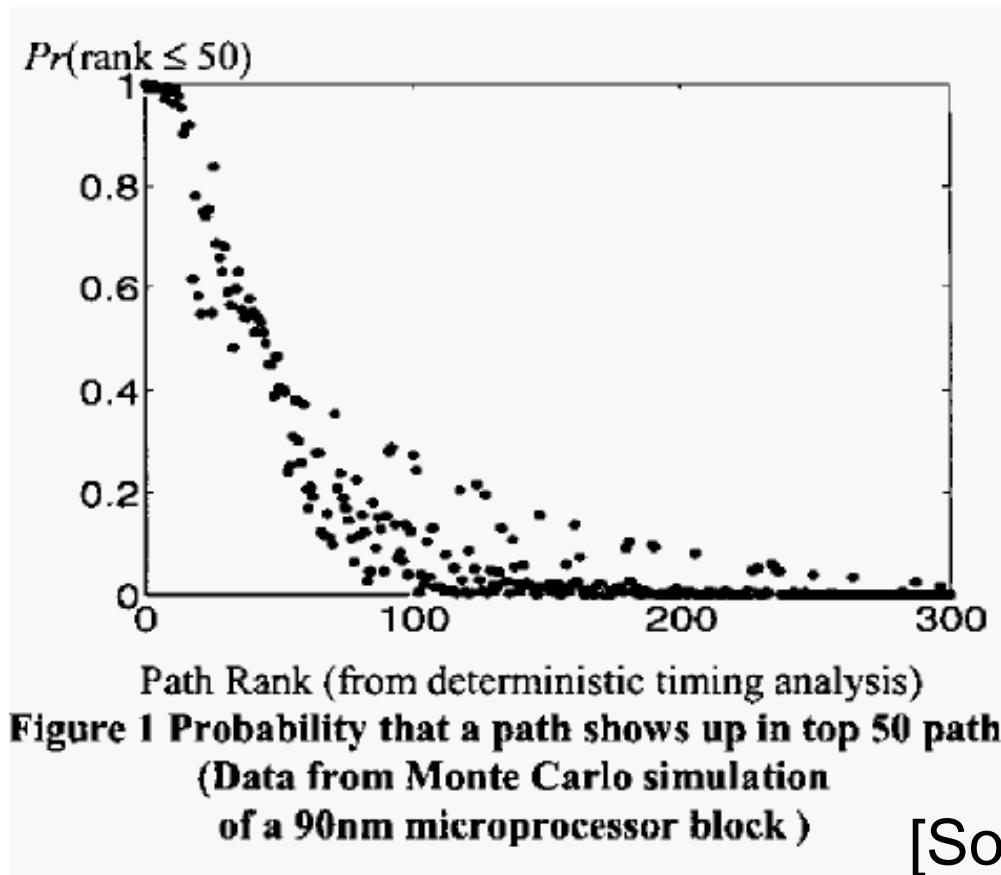


# Does Worst-Case Mislead?

- Delay of off-critical path may matter
- Best case delay of critical path?
- Worst-case delay of non-critical path?



# Probability of Path Being Critical



# What do we need to do?

- Ideal:
  - Compute PDF for delay at each gate
  - Compute delay of a gate as a PDF from:
    - PDF of inputs
    - PDF of gate delay

# Delay Calculation

AND rules

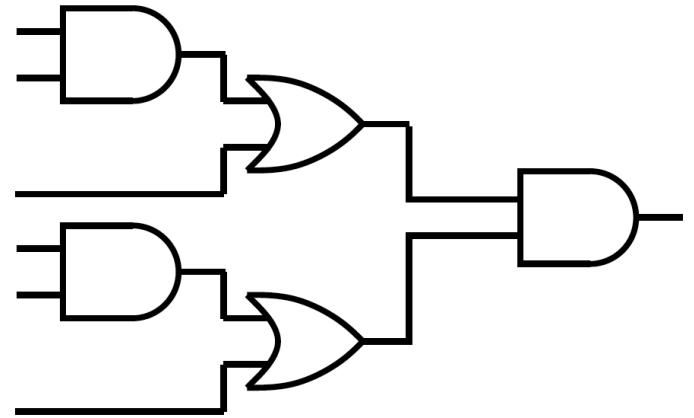
$i_1 \rightarrow$ $i_2 \downarrow$	0	1	2
0	$MIN(l_1, l_2) + d$ $MIN(u_1, u_2) + d$	$l_2 + d$ $u_2 + d$	$MIN(l_1, l_2) + d$ $u_2 + d$
1	$0$ $l_1 + d$ $u_1 + d$	$1$ $MAX(l_1, l_2) + d$ $MAX(u_1, u_2) + d$	$2$ $l_1 + d$ $MAX(u_1, u_2) + d$
2	$0$ $MIN(l_1, l_2) + d$ $u_1 + d$	$2$ $l_2 + d$ $MAX(u_1, u_2) + d$	$2$ $MIN(l_1, l_2) + d$ $MAX(u_1, u_2) + d$

# What do we need to do?

- Ideal:
  - compute PDF for delay at each gate
  - Compute delay of a gate as a PDF from:
    - PDF of inputs
    - PDF of gate delay
  - Need to compute for distributions
    - SUM
    - MAX (maybe MIN)

# For Example

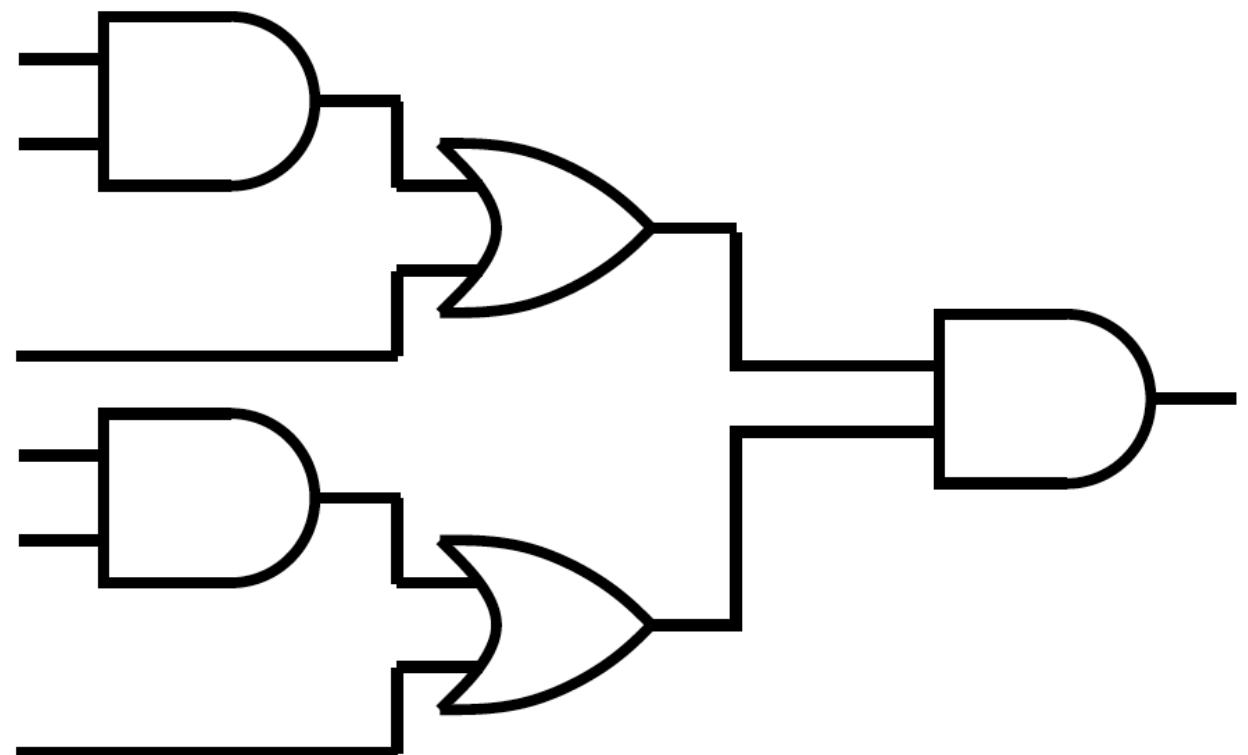
- Consider entry:  
–  $\text{MAX}(u_1, u_2) + d$



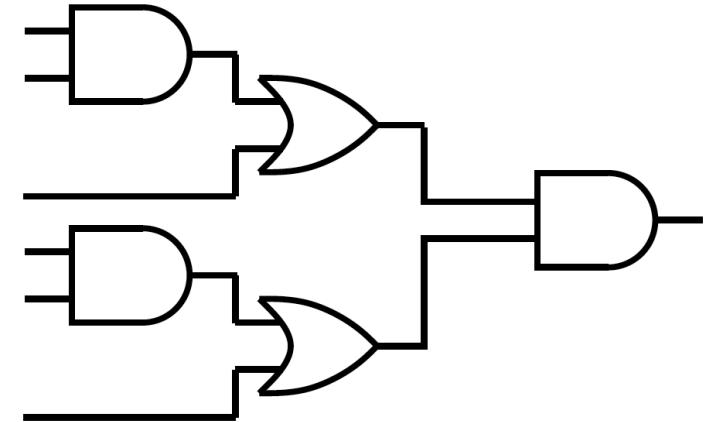
$i_1 \rightarrow$ $i_2 \downarrow$	0	1	2
0	0 $\text{MIN}(l_1, l_2) + d$ $\text{MIN}(u_1, u_2) + d$	0 $l_2 + d$ $u_2 + d$	0 $\text{MIN}(l_1, l_2) + d$ $u_2 + d$
1	0 $l_1 + d$ $u_1 + d$	1 $\text{MAX}(l_1, l_2) + d$ $\text{MAX}(u_1, u_2) + d$	2 $l_1 + d$ $\text{MAX}(u_1, u_2) + d$
2	0 $\text{MIN}(l_1, l_2) + d$ $u_1 + d$	2 $l_2 + d$ $\text{MAX}(u_1, u_2) + d$	2 $\text{MIN}(l_1, l_2) + d$ $\text{MAX}(u_1, u_2) + d$

# MAX

- Compute MAX of two input distributions
  - Preclass 2(b)



SUM



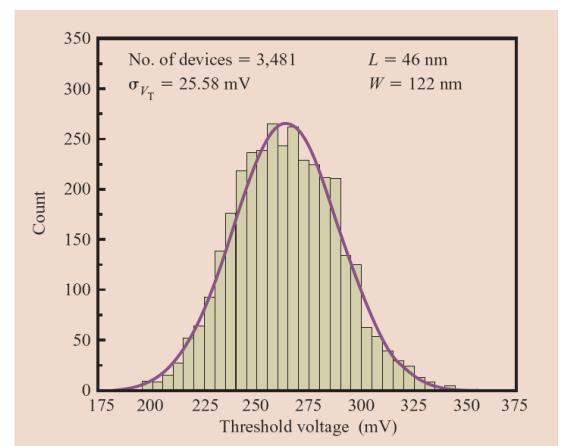
- Add that distribution to gate distribution.

# Continuous

- Can roughly carry through PDF calculations with Gaussian distributions rather than discrete PDFs

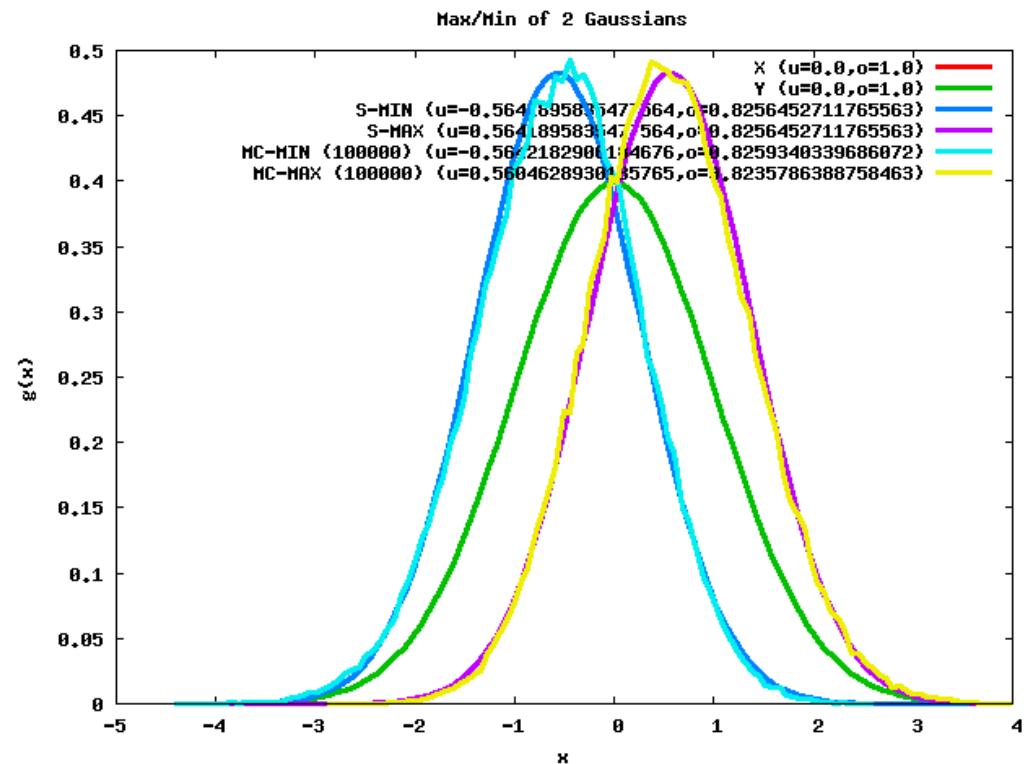
# Dealing with PDFs

- Simple model assume all PDFs are Gaussian
  - Model with mean,  $\sigma$
  - Imperfect
    - Not all phenomena are Gaussian
    - Sum of Gaussians is Gaussian
    - Max of Gaussians is **not** a Gaussian



# MAX of Two Identical Gaussians

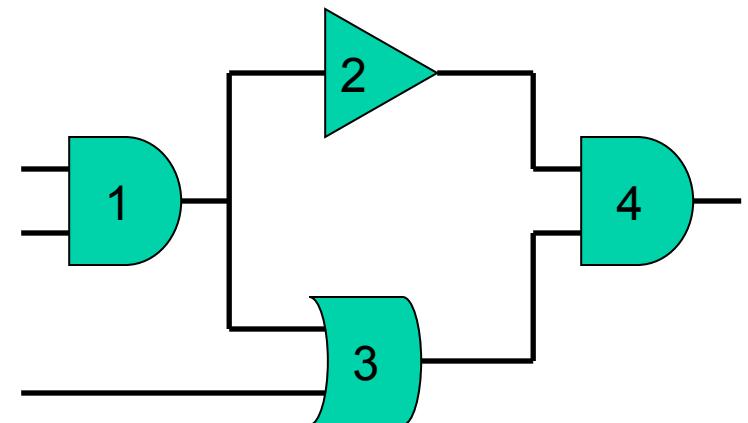
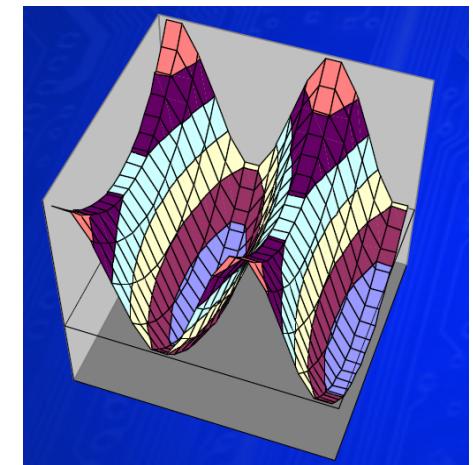
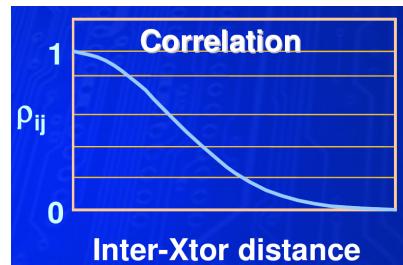
- Max of Gaussians is not a Gaussian
- Can try to approximate as Gaussian
- Given two identical Gaussians A and B with  $\mu$  and  $\sigma$
- Plug into equations
- $E[\text{MAX}(A,B)] = \mu + \sigma/(\pi)^{1/2}$
- $\text{VAR}[\text{MAX}(A,B)] = \sigma^2 - \sigma/\pi$



[Source: Nikil Mehta]

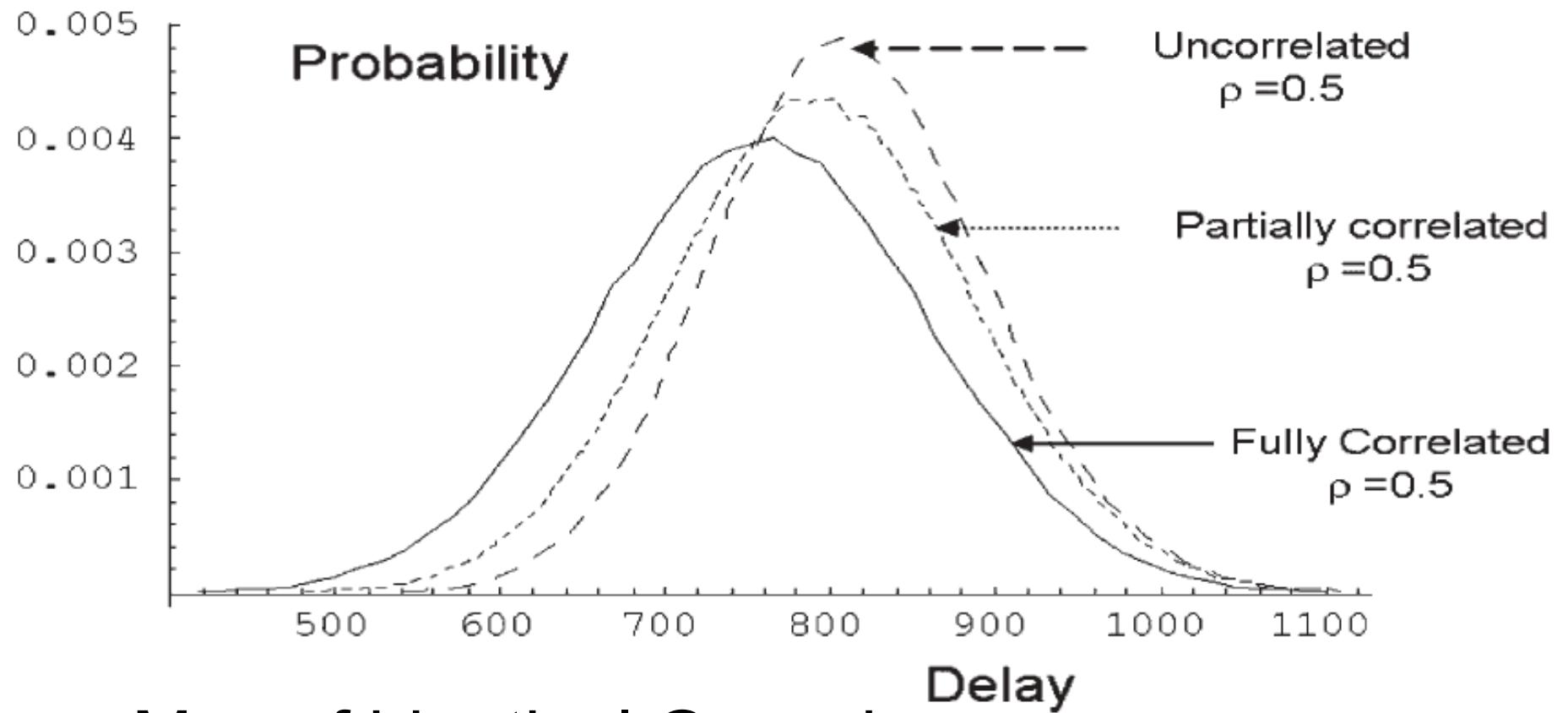
# More Technicalities

- Correlation
  - Physical on die
  - In path (reconvergent fanout)
    - Makes result conservative
    - Gives upper bound
    - Can compute lower



Graphics from: Noel Menezes (top) and Nikil Mehta (bottom)

# Max of Gaussians with Correlation

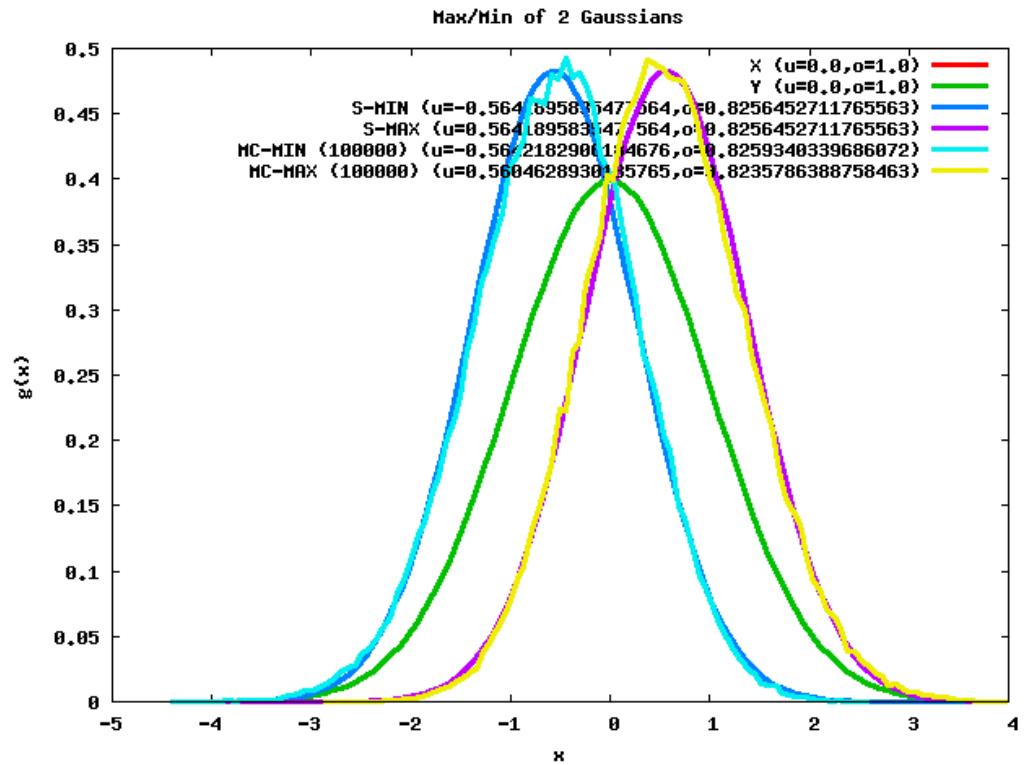


- Max of identical Gaussians

# MAX of Two Identical Gaussians

- Given two identical Gaussians A and B with  $\mu$  and  $\sigma$
- Plug into equations
- $E[\text{MAX}(A,B)] = \mu + \sigma/(\pi)^{1/2}$
- $\text{VAR}[\text{MAX}(A,B)] = \sigma^2 - \sigma/\pi$

[Source: Nikil Mehta]



Extreme of correlated: is just the input Gaussian

# SSTA vs. Monte Carlo Verification Time

TABLE II  
MONTE CARLO VERSUS EinsStat COMPARISON

Test case	Gates	EinsStat CPU	Monte Carlo		
			Samples	Sequential CPU dd:hh:mm:ss	Parallel CPU dd:hh:mm:ss
1	18	1 sec.	100000	5:57	N/A
2	3042	2 sec.	100000	2:01:15:10	2:46:55
3	11937	7 sec.	10000	0:20:33:40	51:05
4	70216	59 sec.	10000	N/A	4:36:12

Source: IBM, TRCAD 2006

# Using SSTA in FPGA CAD

[Slide composed  
by Nikil Mehta]

- Le Hei
  - FPGA2007
  - SSTA Synthesis,  
Place, Route
- Kia
  - FPGA2007
  - Route with  
SSTA

process variation settings ( $3\sigma$ )						
	5.0%	10.0%	15.0%	20.0%	25.0%	30.0%
global	5.0%	10.0%	15.0%	20.0%	25.0%	30.0%
spatial	5.0%	10.0%	15.0%	20.0%	25.0%	30.0%
local	3.0%	6.0%	9.0%	12.0%	15.0%	18.0%
deterministic flow						
Tmean (ns)	21.7	22.9	24.4	26.2	28.2	30.2
Tsigma (ns)	1.8	3.4	5.0	6.4	7.8	9.2
stochastic flow						
Tmean (ns)	20.3 (-6.5%)	21.5 (-6.2%)	23.0 (-5.8%)	24.8 (-5.5%)	26.7 (-5.3%)	28.6 (-5.1%)
Tsigma (ns)	1.6 (-6.6%)	3.1 (-7.5%)	4.6 (-8.1%)	5.9 (-8.2%)	7.2 (-8.1%)	8.5 (-8.0%)

Table 6: Comparison of mean delay and standard deviation between deterministic and stochastic flows under various process variation assumptions (based on the geometric mean of 20 MCNC designs).

Circuit	Delay Impr. (%)
ex5p	6.58
alu4	1.50
misex3	5.76
apex2	3.24
apex4	2.57
pdc	4.74
seq	4.37
des	3.73
spla	4.82
ex1010	1.83
frisc	2.84
elliptic	0.17
bigkey	0.35
s298	7.10
tseng	5.93
diffeq	4.16
dsip	7.37
s38417	7.56
s38584.1	5.43
clma	-1.17
Mean	3.95

# Impact of SSTA in High-Level Synthesis

Design (#ops)	#ALU, #MUL	$p_{clk}$ (ns)	Latency(cycles)		Reduction	Run time(s)
			LS[15]	HLS-tv(Y)		
DIFF (18)	3, 3	3.5	32	28 (94.5%)	12.5%	928
		4.0	29	24 (90.7%)	17.2%	930
		4.5	26	22 (93.2%)	15.4%	637
LATT (22)	3, 2	3.5	47	36 (94.3%)	23.4%	2122
		4.0	42	32 (94.3%)	23.8%	3325
		4.5	37	30 (90.2%)	18.9%	1207
AR (28)	2, 3	3.5	57	45 (93.9%)	21.1%	1241
		4.0	51	40 (93.9%)	21.6%	1534
		4.5	45	36 (90.8%)	20.0%	680
EWF (34)	2, 3	3.5	46	37 (93.6%)	19.6%	157
		4.0	42	34 (93.6%)	19.0%	367
		4.5	38	33 (91.5%)	13.2%	113
avg.				- (92.9%)	18.8%	

- Scheduling and provisioning
  - ALU/MUL  $\sigma=5\%$   $t_{nominal}$

# Summary

- Nanoscale fabrication is a statistical process
- Delays are PDFs
- Assuming each device is worst-case delay is too pessimistic
  - Wrong prediction about timing
  - Leads optimization in wrong direction
- Reformulate timing analysis as statistical calculation
- Estimate the PDF of circuit delays
- Use this to drive optimizations

# Big Ideas:

- Coping with uncertainty
- Statistical Reasoning and Calculation

# Admin

- Reading for Monday on canvas
- Milestone Thursday